



Wavefront correction to improve the focused intensity of 10 PW SULF Laser

Xiaoyan Liang Lianghong Yu Yuxin Leng Ruxin Li

Shanghai Institute of Optics and fine Mechanics



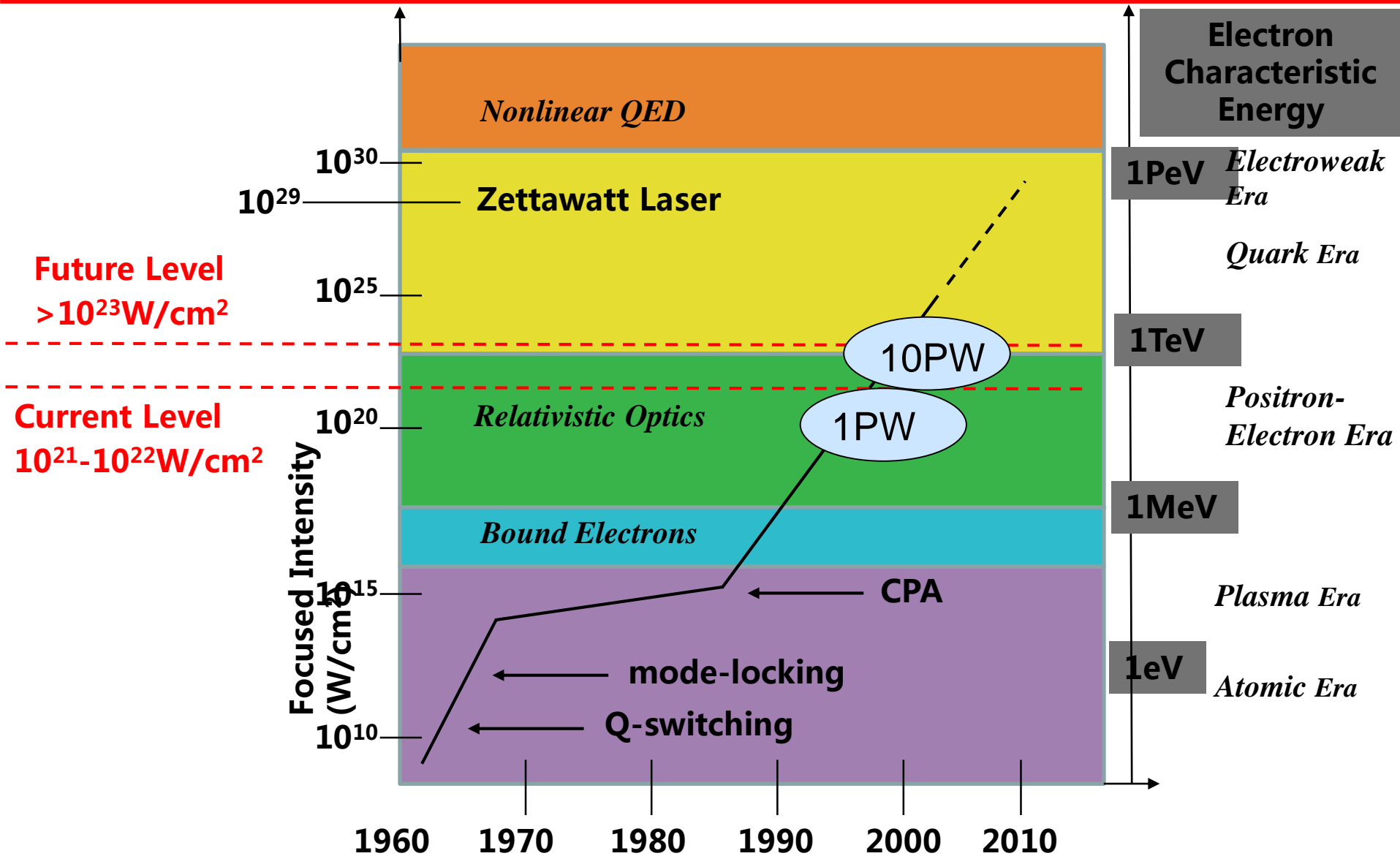
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Shanghai Institute of Optics and Fine Mechanics, CAS

2020-12-01

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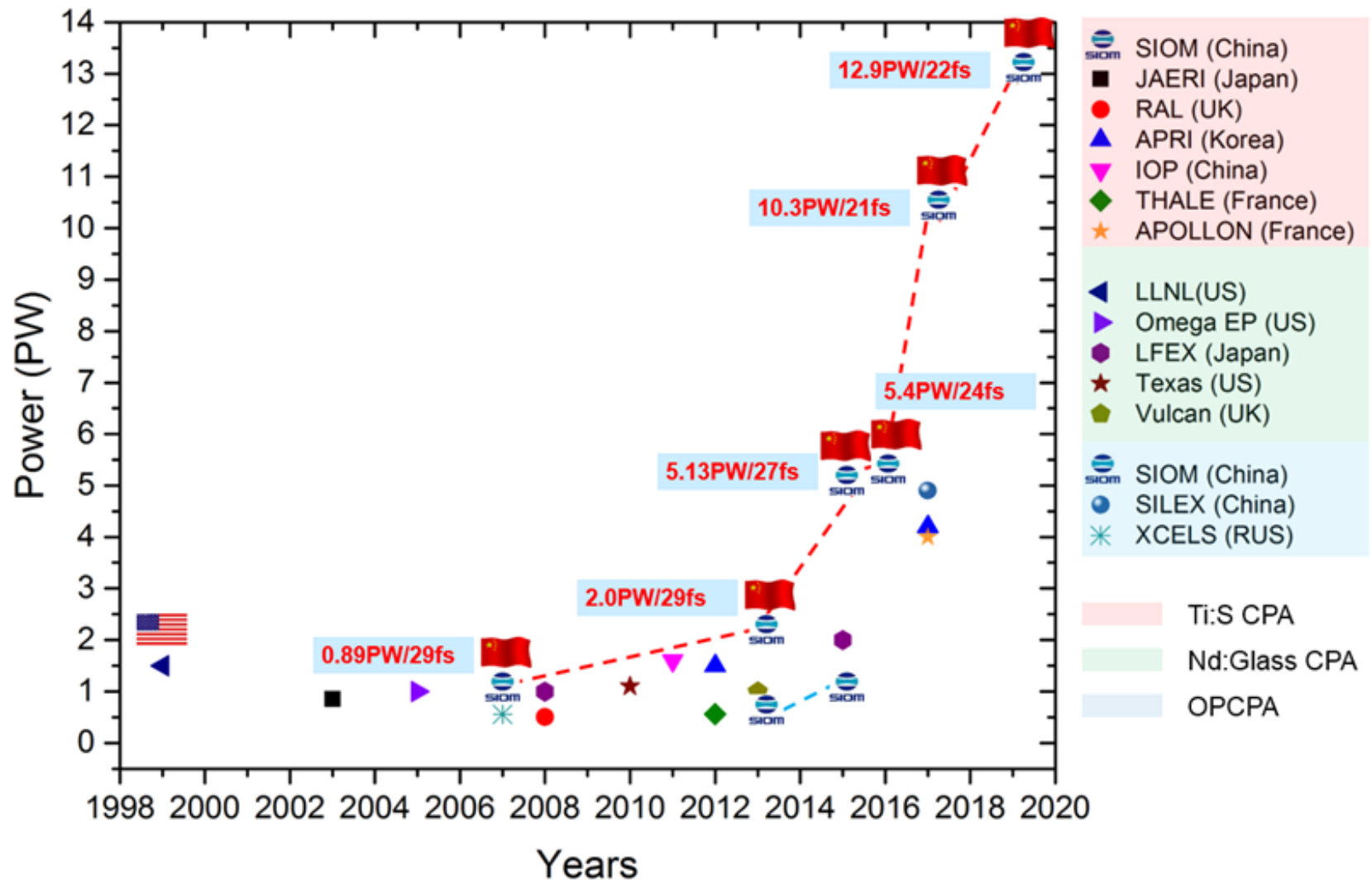
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- 3 **Wavefront correction of 5.4 PW**
- 4 **Wavefront correction of 10 PW**
- 5 **Summary**

Background



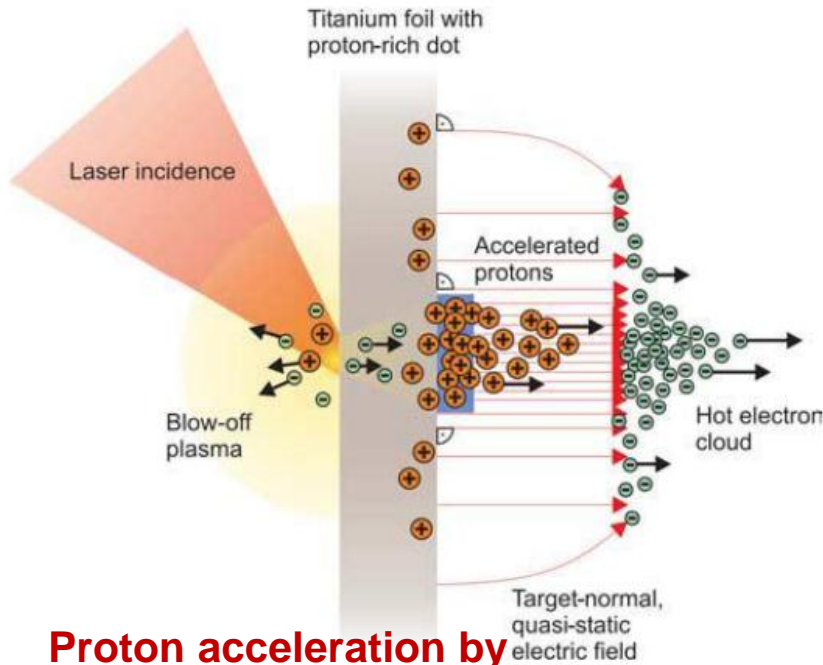
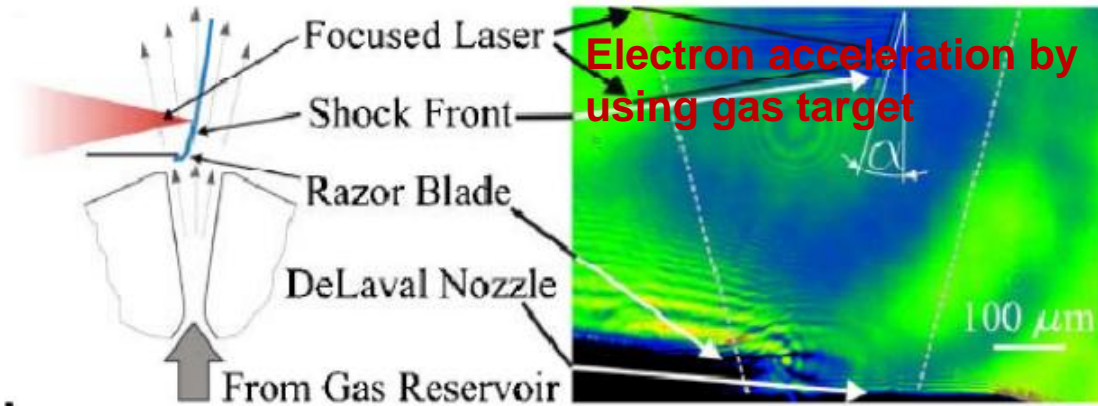
Background

Development of Petawatt laser since the invention of CPA



Background

The **focal intensity** at the target plane is a critical parameter for high-field laser-matter interaction experiments.



Proton acceleration by using solid target

$$P_0 = E_0 / \tau_{\text{eff}} \cdot$$

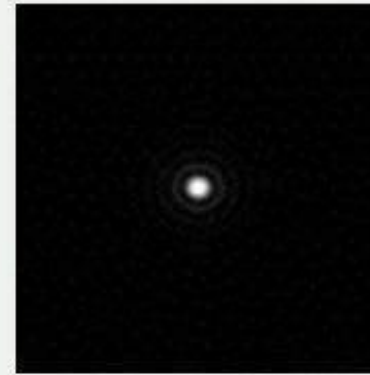
$$I_0 = \frac{E_0}{A_{\text{eff}} \tau_{\text{eff}}} = \frac{E_0}{\pi \cdot r_{\text{eff}}^2 \tau_{\text{eff}}}$$

P_0 : laser Power (PW)

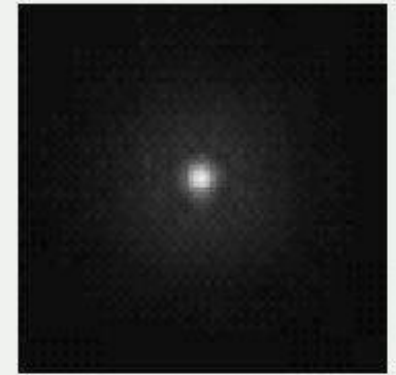
I_0 : Focal intensity

Background

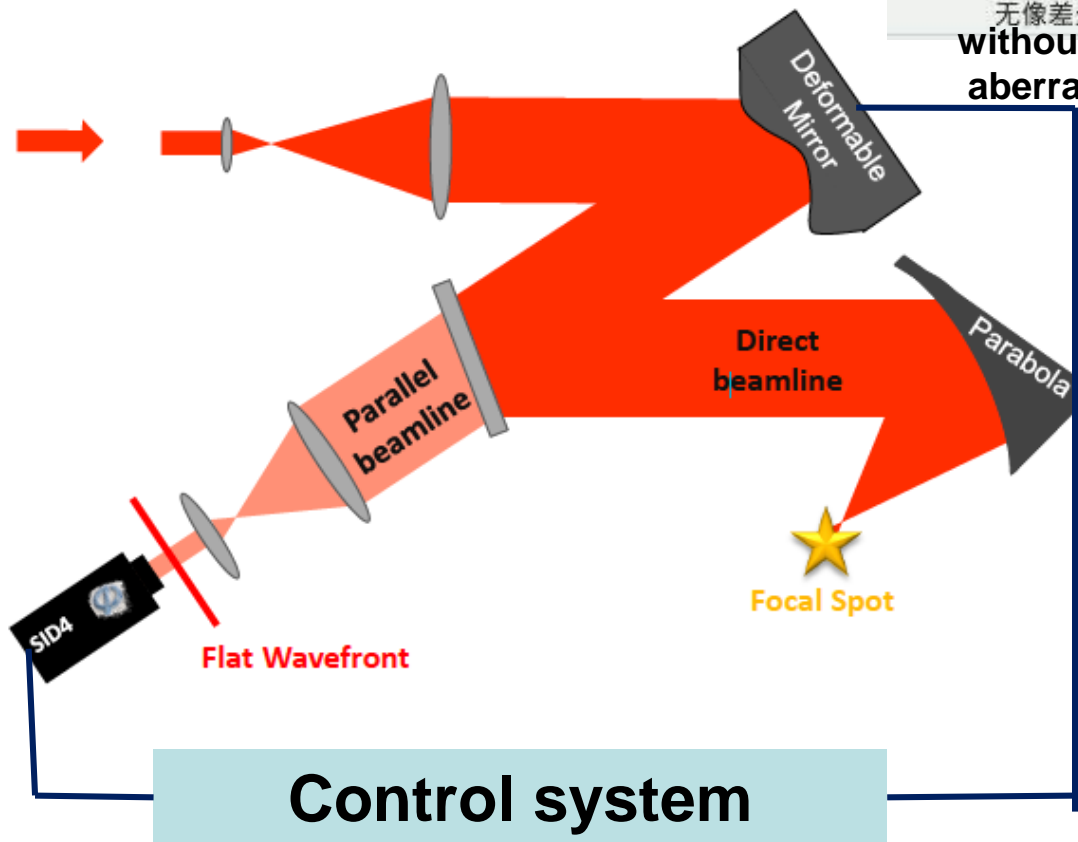
Focal spot size is related to wavefront aberrations of laser pulse and the F number (f/D) of focus element.



无像差光学系统
without wavefront
aberration



有像差的光学系统
with wavefront
aberration



AOS:
Adaptive optical
system

Background

Year	Facility/ Lab/Country	Output Power	AO system	F number of OAP	Focal spot size (FWHM)	Focal intensity
2004/ 2008	HERCULES laser/ <i>University of Michigan team</i> / USA	45TW/ 300TW	1	F#0.6/ F#=1.3	0.8um/ 1.3 um	1×10^{22} W/cm ² / 2×10^{22} W/cm ² [1],[2]
2017	J-KAREN-P laser facility / <i>Kansai Photon Science Institute</i> / Japan	300 TW	1	F#1.3	~ 1.3 μ m	$\sim 10^{22}$ W/cm ² [3]
2018	SULF/ <i>SIOM</i> / China	5.4 PW	2	F#2.5	$2.75 \times$ $2.87 \mu\text{m}^2$	2×10^{22} W/cm ² [4]
2019	Texas Petawatt Laser / <i>University of Texas at Austin</i> , USA	80-120J/ 150 ± 20 f s	1	F#1	~1.32um	$\geq 10^{22}$ W/cm ² [5]
2019	multi-PW laser/ <i>Center for Relativistic Laser Science</i> / South Korea	4.2PW	2	F#1.6	~ $1.5 \times 1.$ $8 \mu\text{m}^2$	5.5×10^{22} W/cm ² [6]

[1].Opt. Lett. 29, 2837(2004); [2] Opt.Express 16, 2109 (2008); [3] Opt. Express 25, 20486 (2017);
[4] Opt.Express 26, 26776 (2018); [5] Opt. Lett. 44, 2764(2019) ; [6] Opt. Express 27, 20412 (2019);

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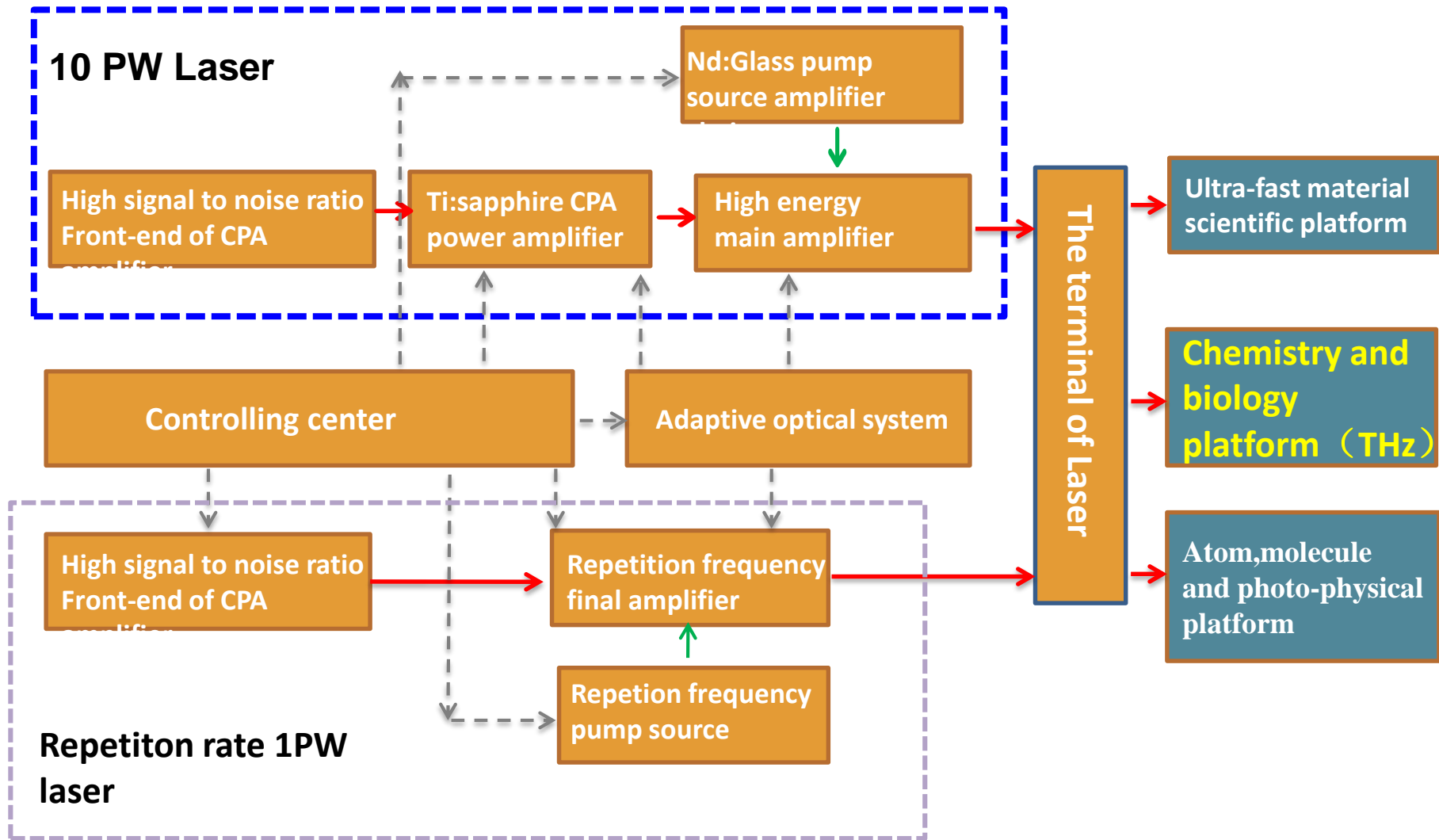
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SULF — 10PW



SULF Project



SULF

Control Center

10PW Laser

Repetition 1PW Laser

Chemistry and Biology Platform (THz)

Design

Data center

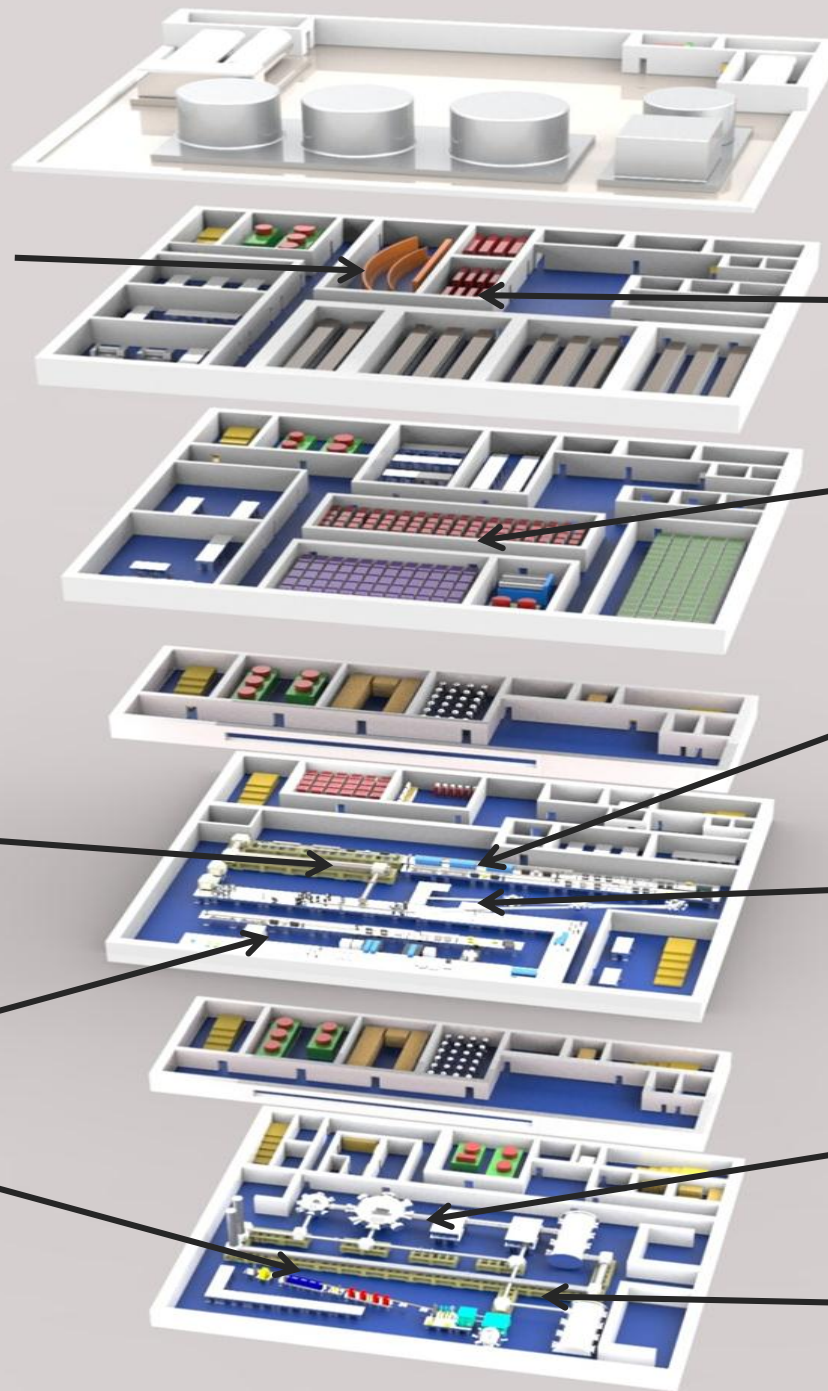
Power supply

Nd:glass pump source

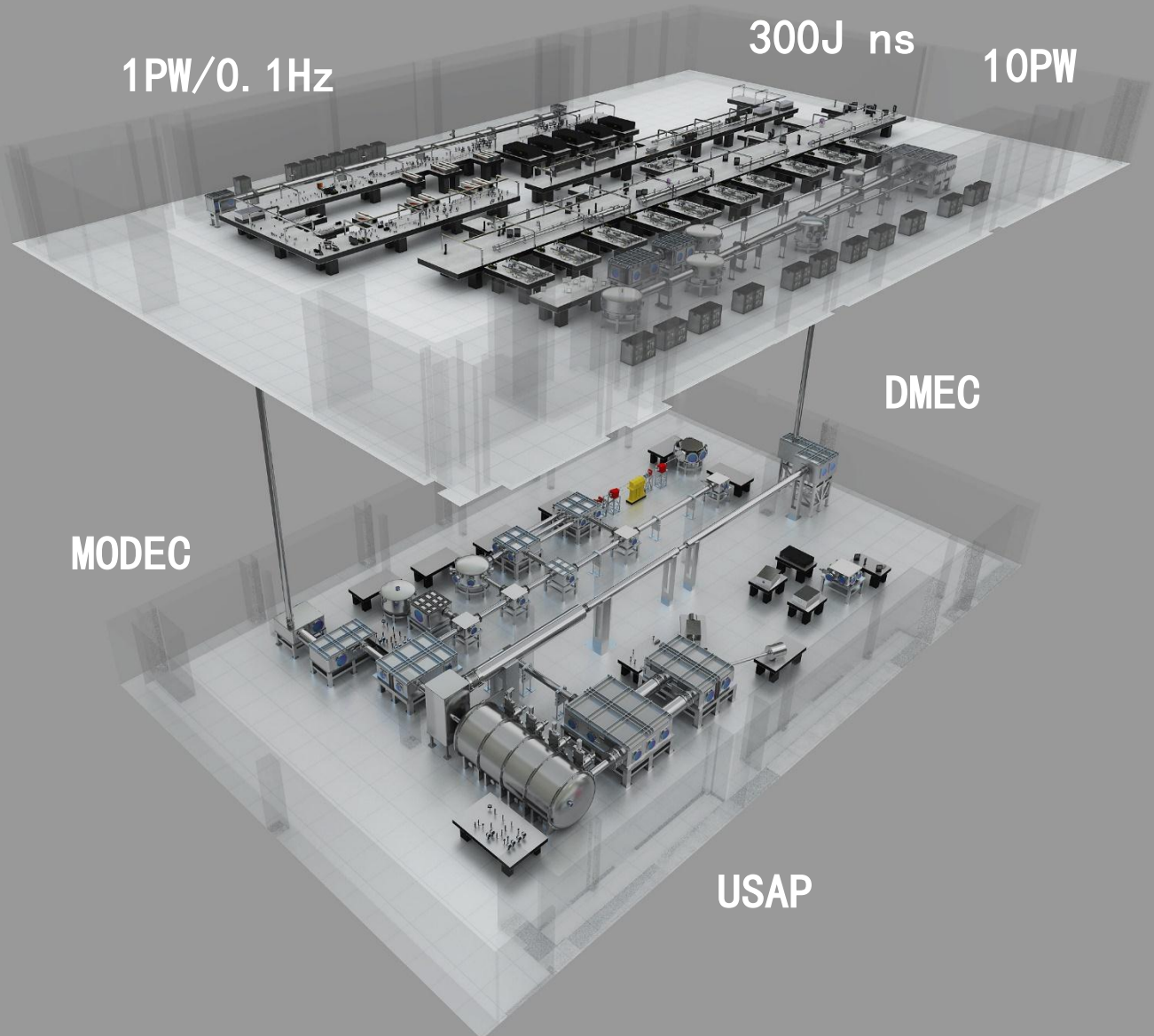
Ultrafast Material Science Platform

Atom, molecule and photo-physics platform

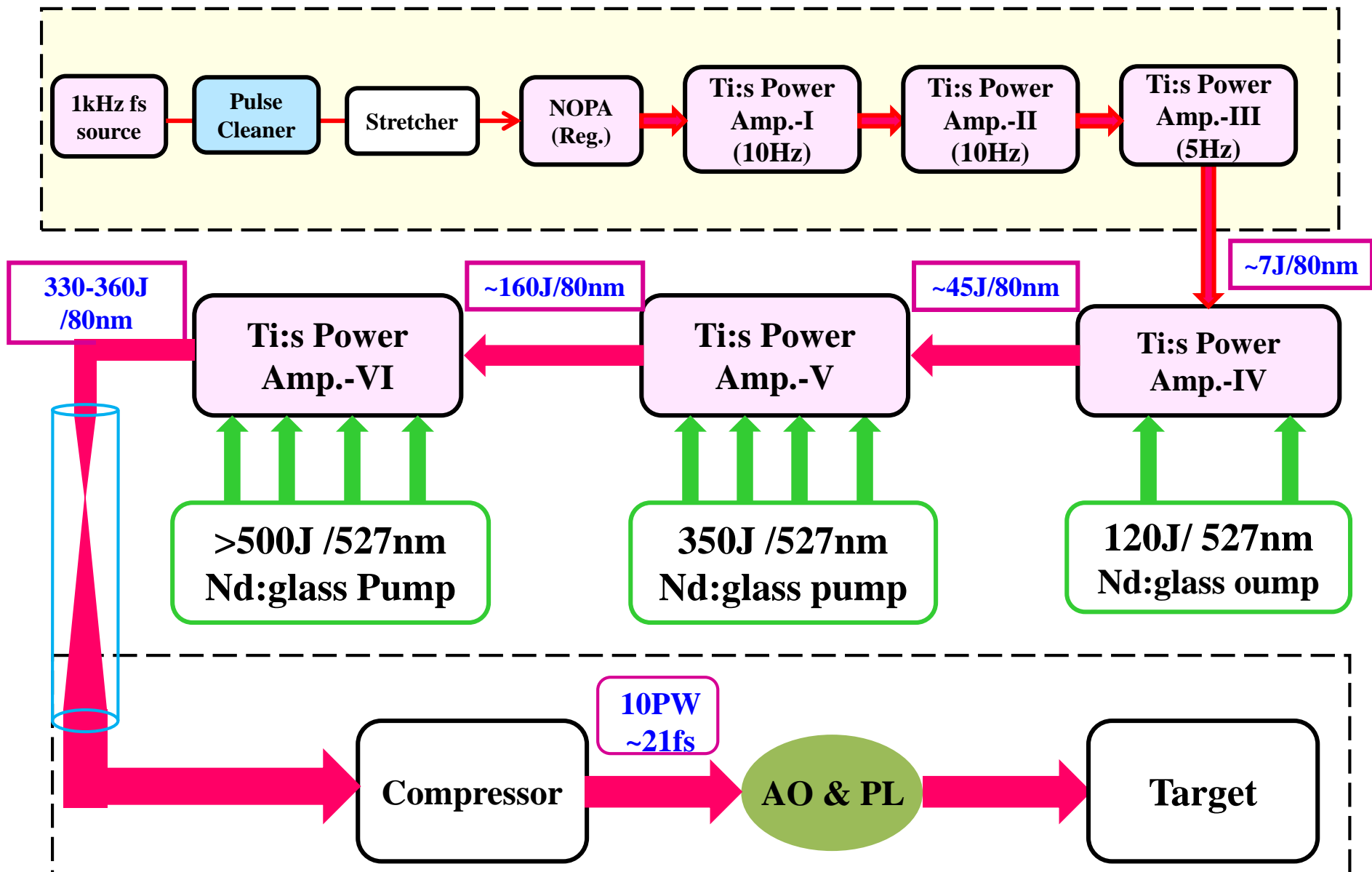
Laser Terminal



Layout of SULF 10PW



Design of 10PW CPA Laser



Ti:Sa Amplifiers of SULF 10PW

Output:

Amplified energy (avg.): 407.9J

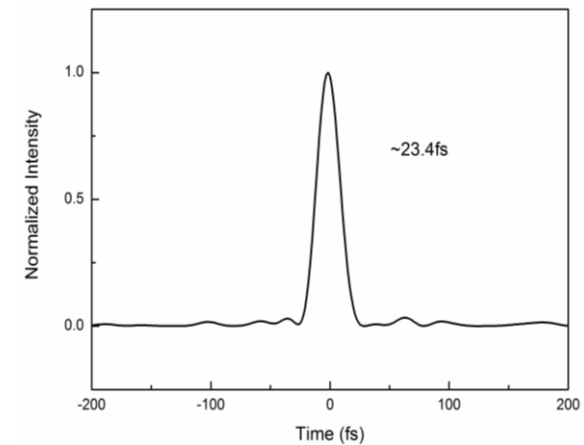
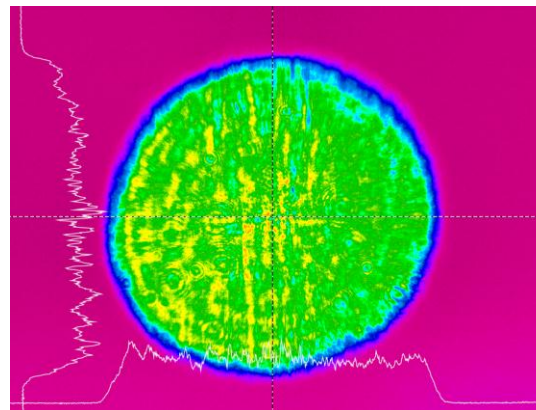
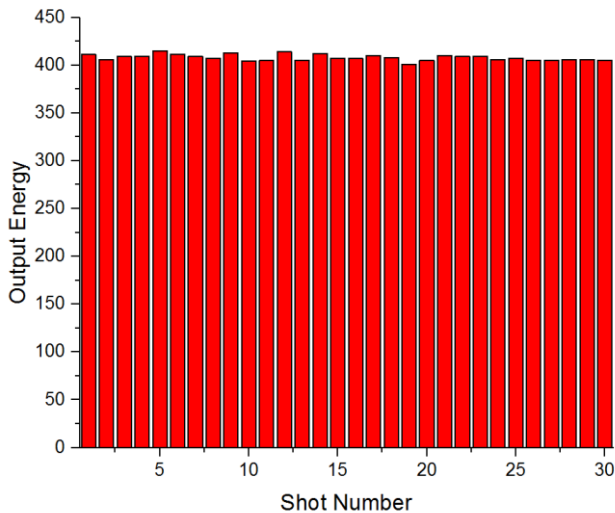
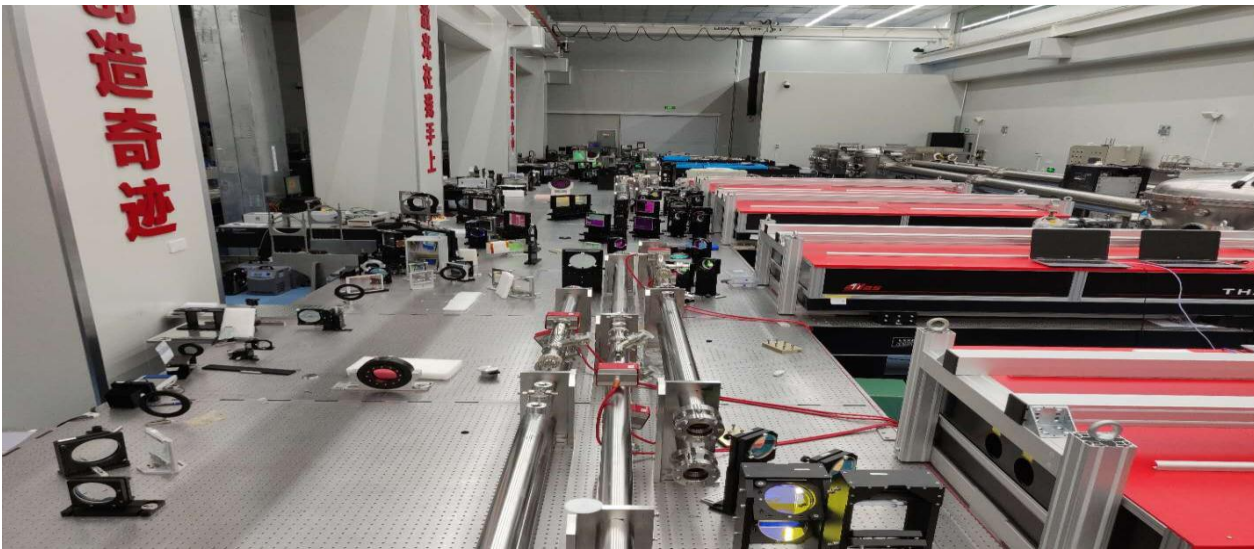
Pump energy (avg.): 529J

Conv. effi. of pump: 47%

Energy stability: 0.8% (RMS)

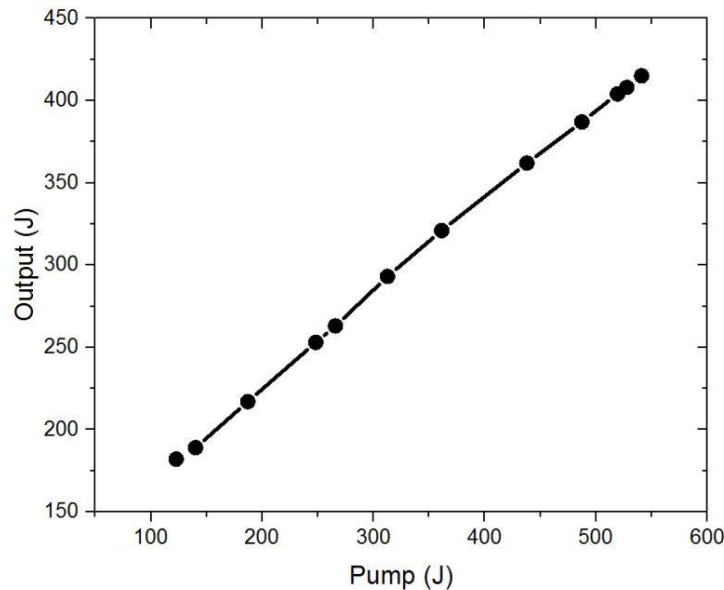
Compressed duration: 23.4fs

Peak power (avg.): 11.7 PW



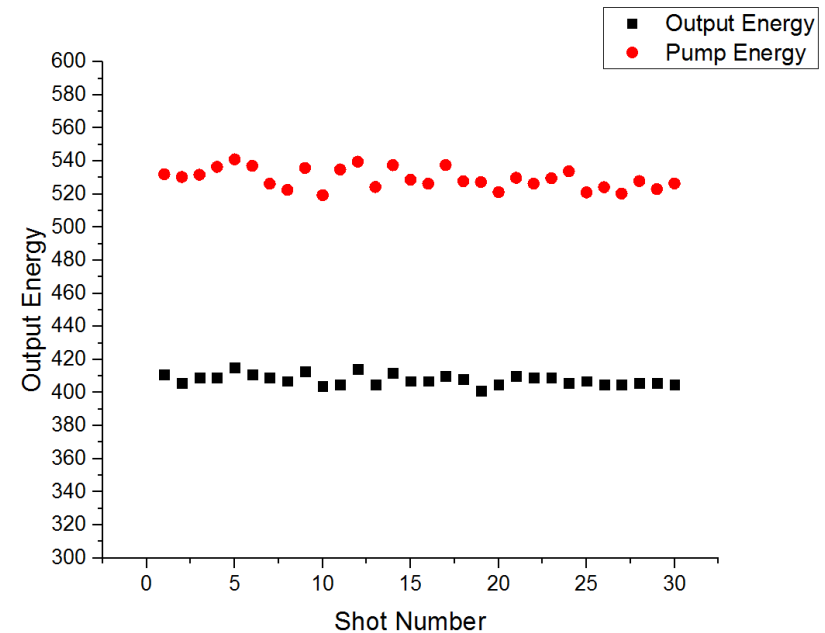
Amplified energy from final amplifier

Output energy vs Pump



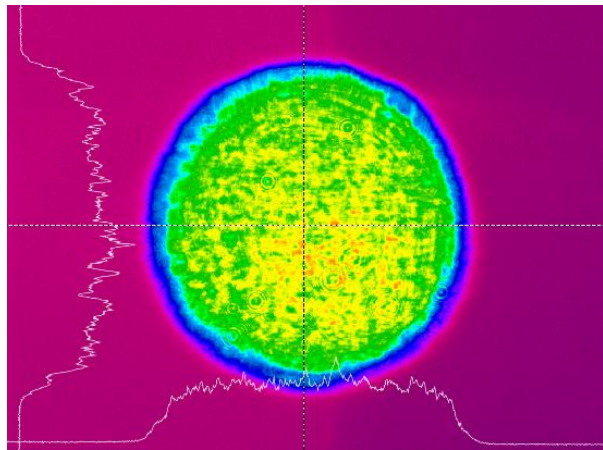
Pump energy: 540J
Injected energy: 160J
Amplified energy: 422J
Conversion efficiency: 43%

Stability of output energy

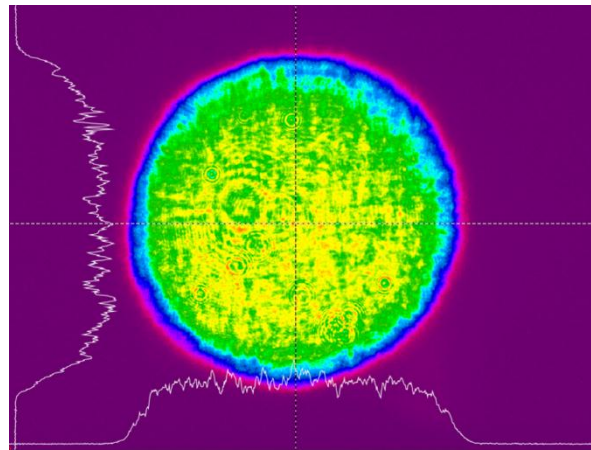


For 30 shots:
Energy: ~408J
RMS: 0.8%

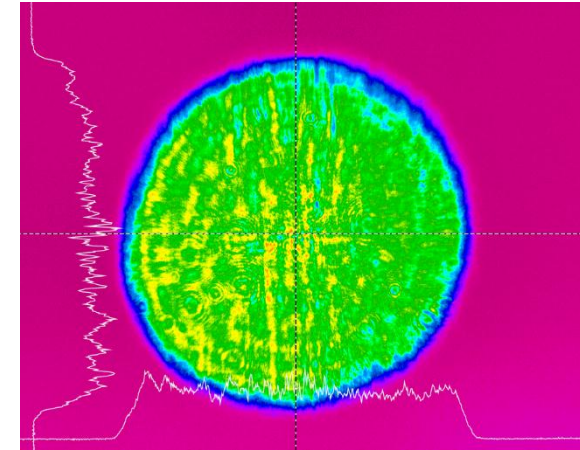
Beam Profile



**Beam Profile at 50J from
 $\phi 100$ Ti:sapphire amp.**

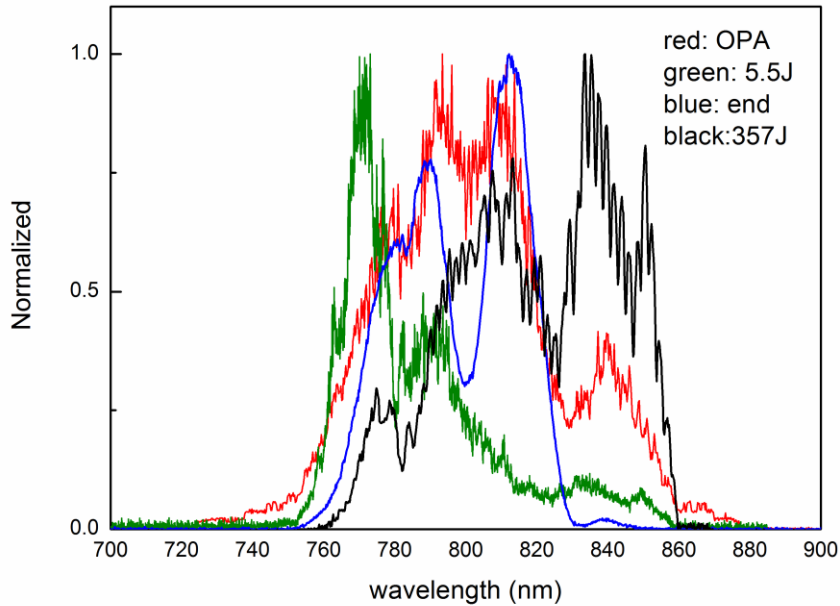


**Beam Profile at 160J from
 $\phi 150$ Ti:sapphire amp.**

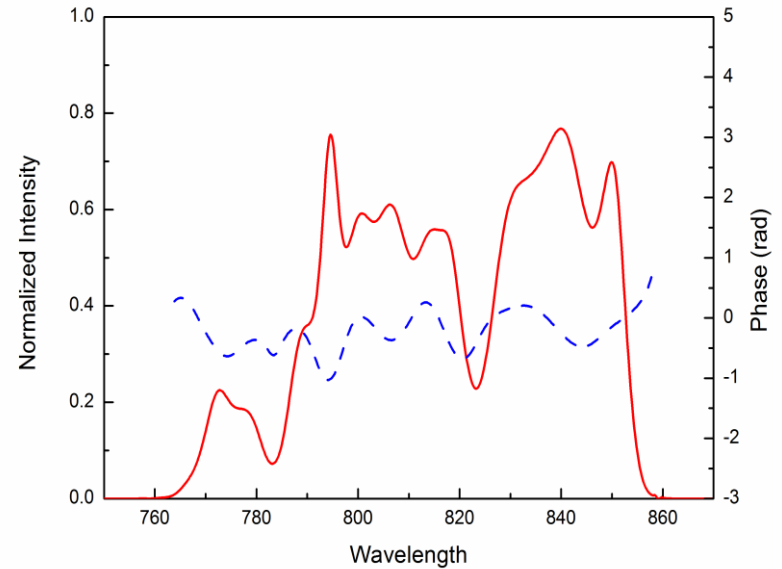


**Beam Profile at 410J from
 $\phi 220$ Ti:sapphire amp.**

Spectrum and dispersion

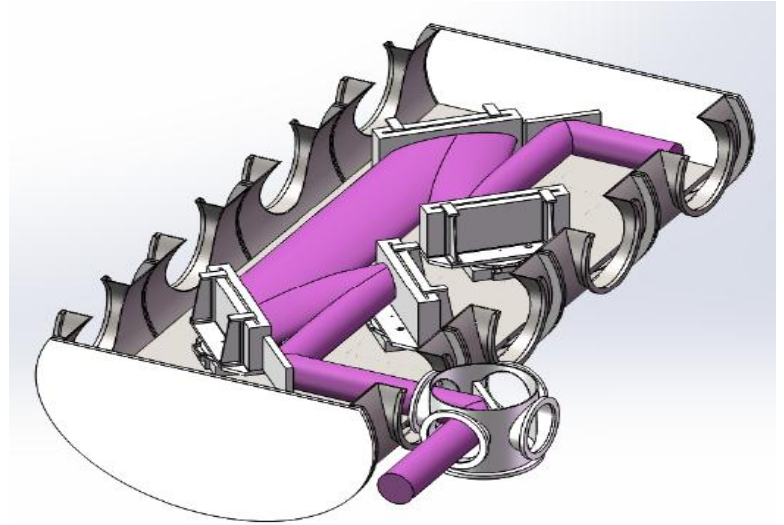


**Full spectrum width at energy of 357J:
760nm—858nm**

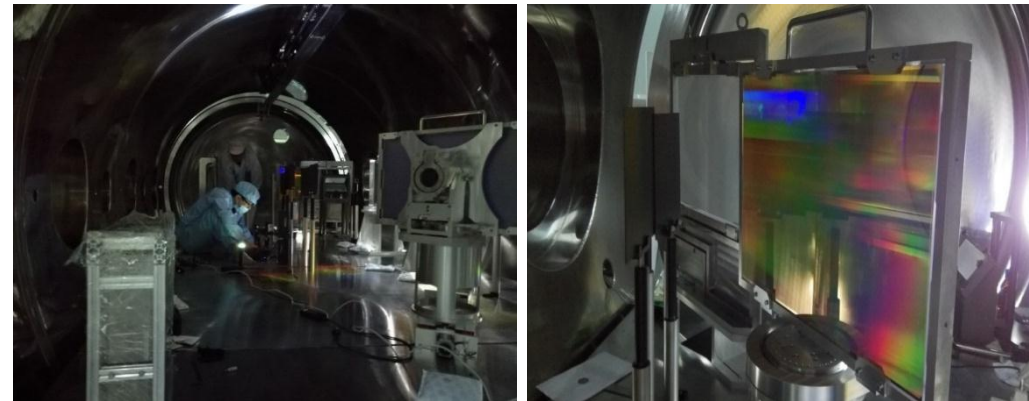


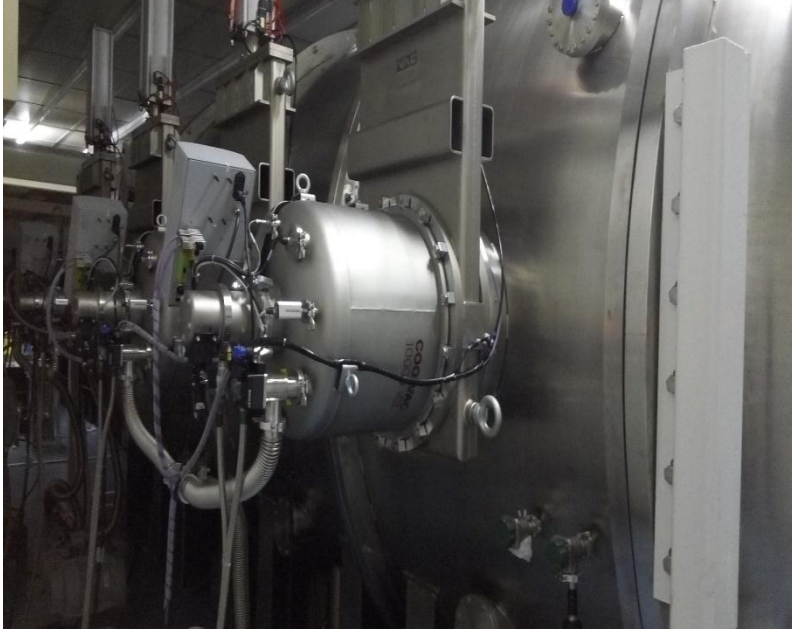
**Active Compensation of
dispersion by Dazzler**

Pulse compression

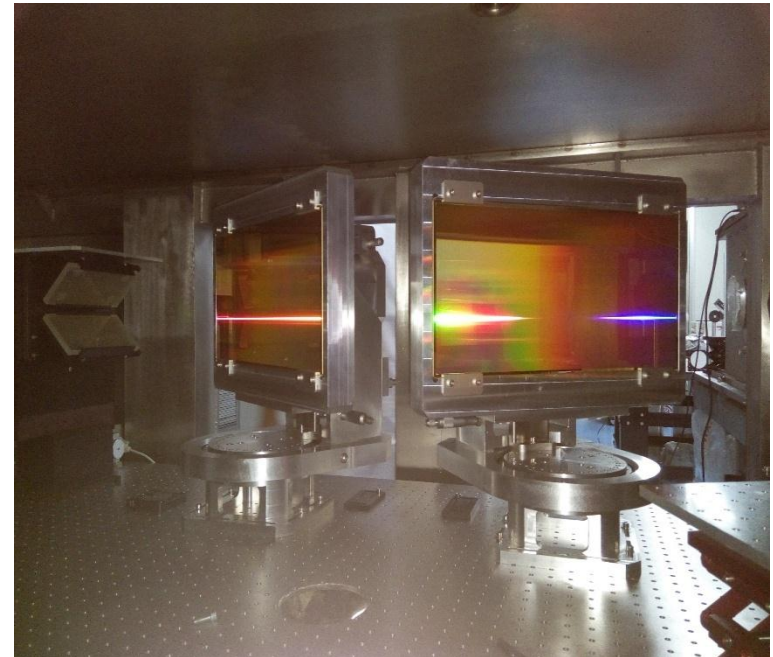
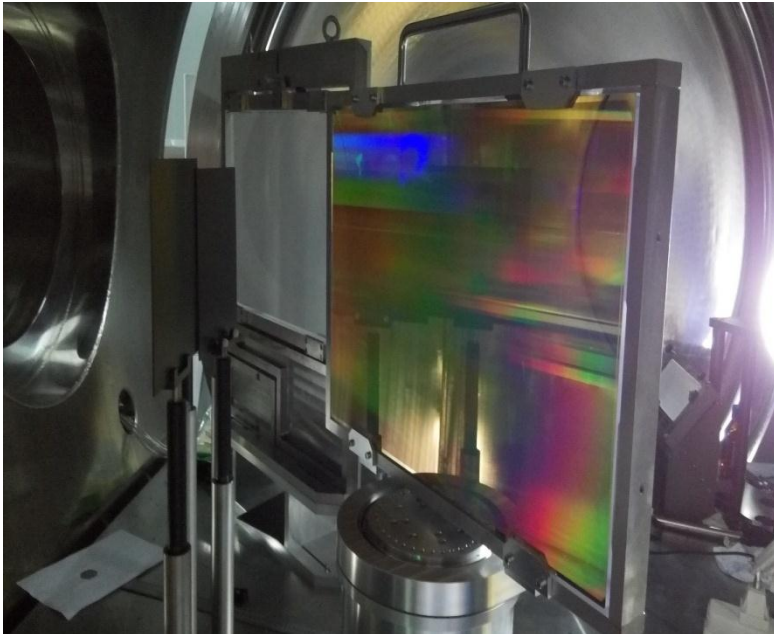


Grating size:
 560×1100 (mm) , 1480 lines/mm
Chamber size: $\phi 2000 \times 6000$ (mm)
Beam size: $\phi 500$ mm
efficiency: ~71.3%

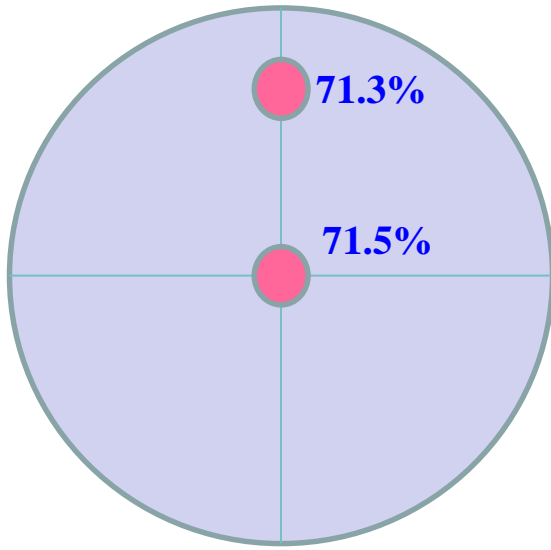




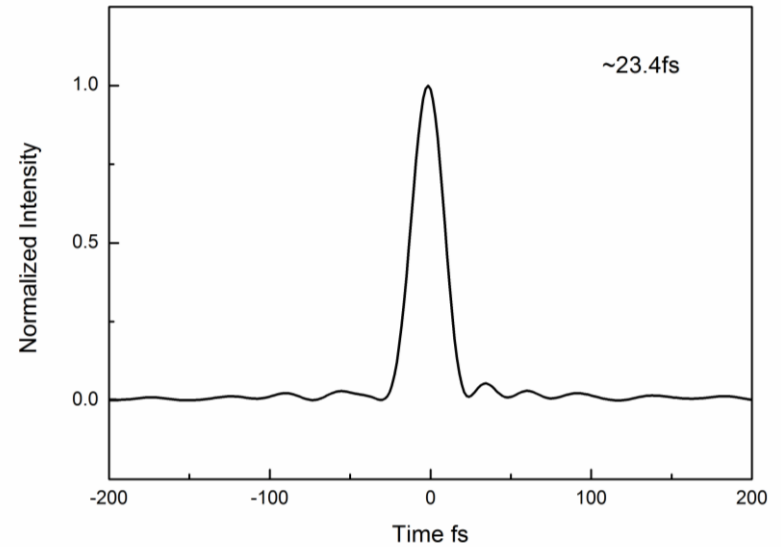
Gratings for 10PW: 1480g/mm, 560mm*1100mm



Pulse Width Measurement



Efficiency measure: 71.3%



Pulse width: 23.4fs

Peak power : $422 \text{ J} \times 71.3\% / 23.4 \text{ fs} = 12.9 \text{ PW}$

SULF-1PW





SULF-10PW

家國在我心中

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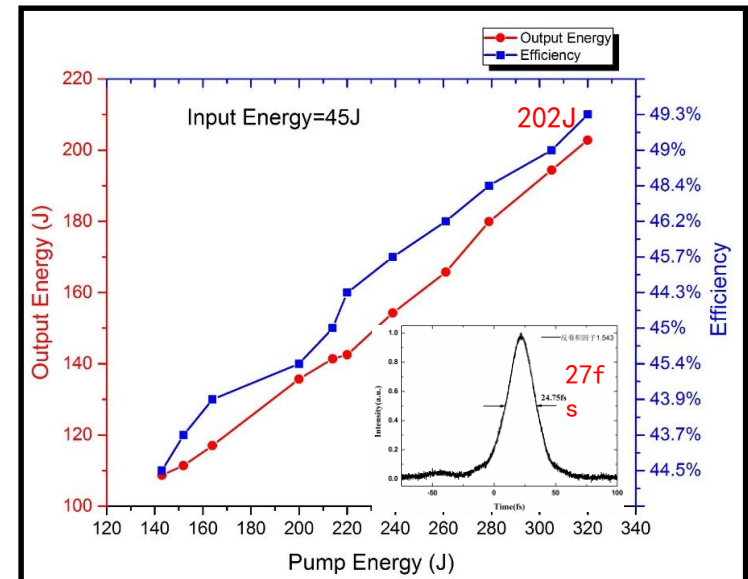
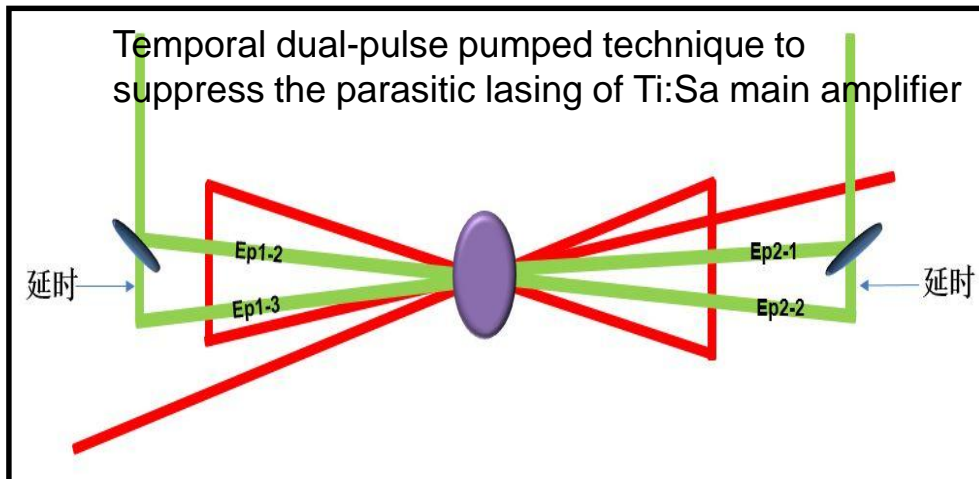
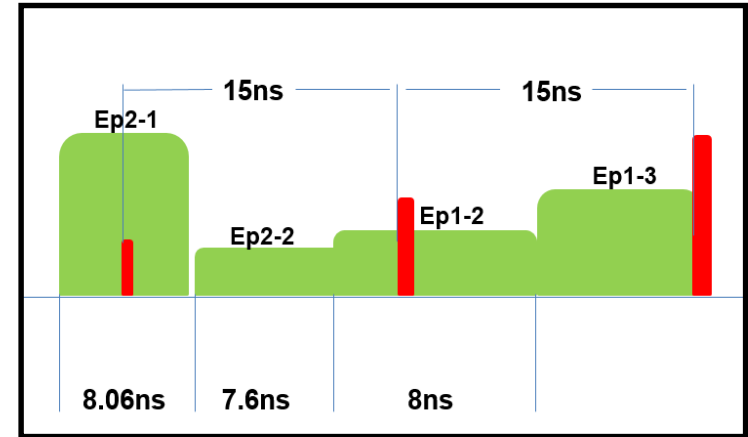
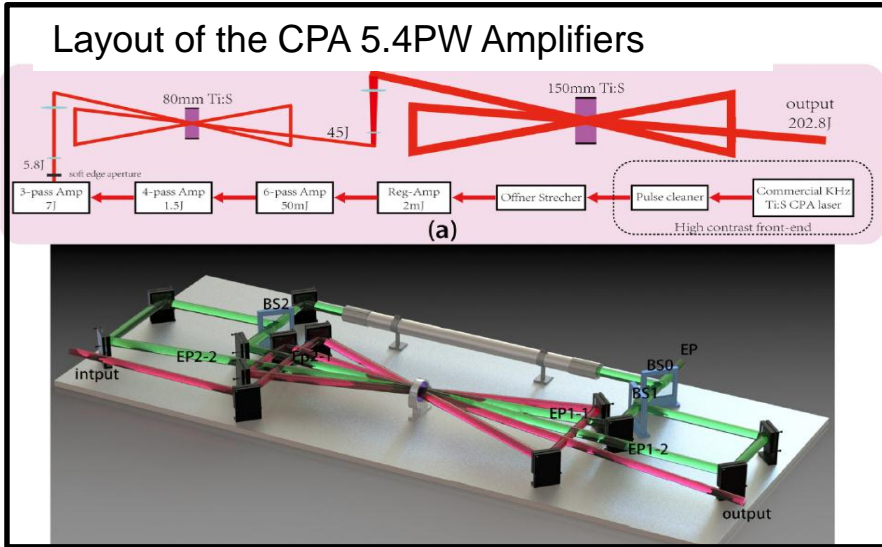
2 SULF Laser

3 Wavefront correction of 5.4 PW

4 Wavefront correction of 10 PW

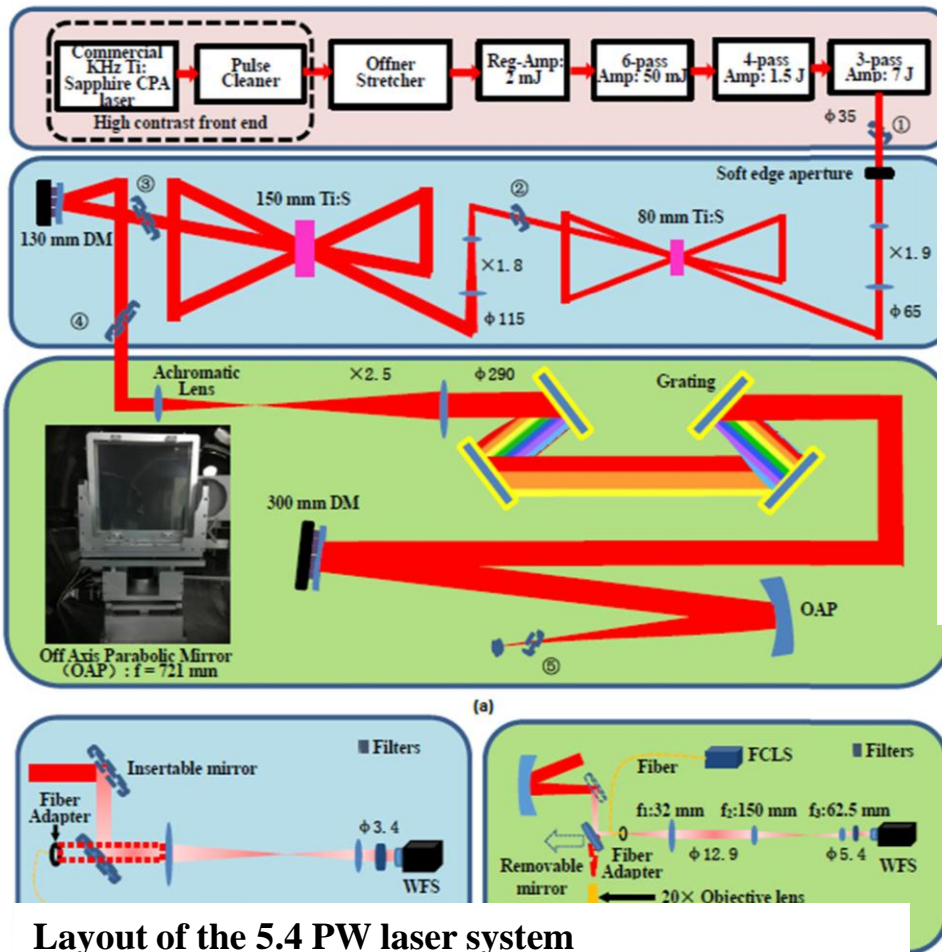
5 Summary

2016



Zebiao Gan[†], Lianghong Yu[†], Shuai Li[†], Xiaoyan Liang*, Yuxin Leng*, Ruxin Li*, and Zhizhan Xu*, et. Opt. Express 25, 5169-5178 (2017)

Evolution of wavefront aberration

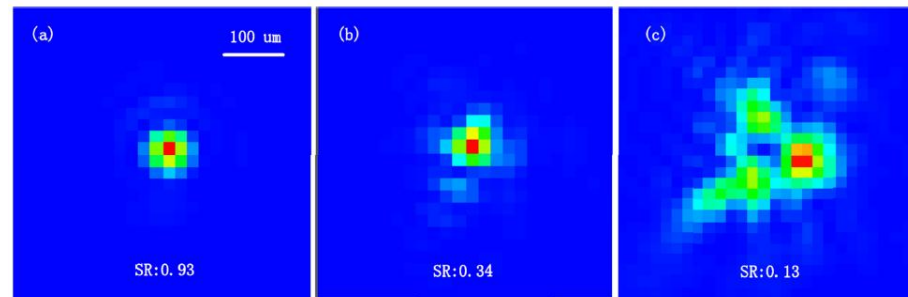
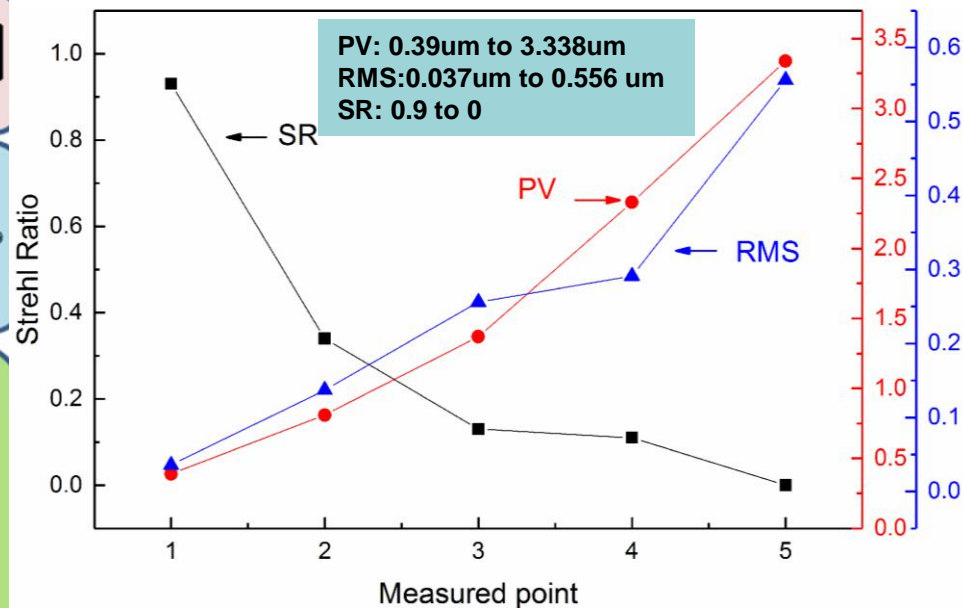


Layout of the 5.4 PW laser system

①- ⑤ : the measured points

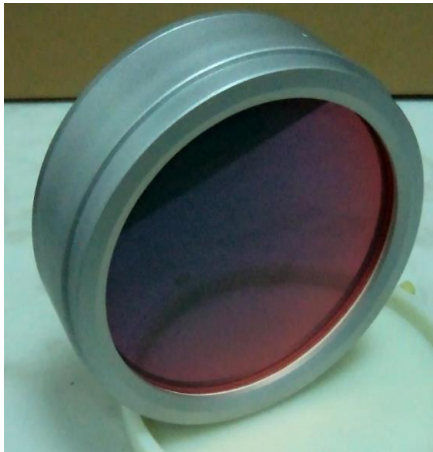
(b) : The insertable sampling optical path for ①- ④;

(c): The sampling optical path for ⑤.



Calculated focal spots by the corresponding wavefront and intensity measured at point ①- ③

Deformable Mirror -1



Deformable mirror



Wavefront sensor

Main technical parameters of the bimorph mirror DM2-130-64

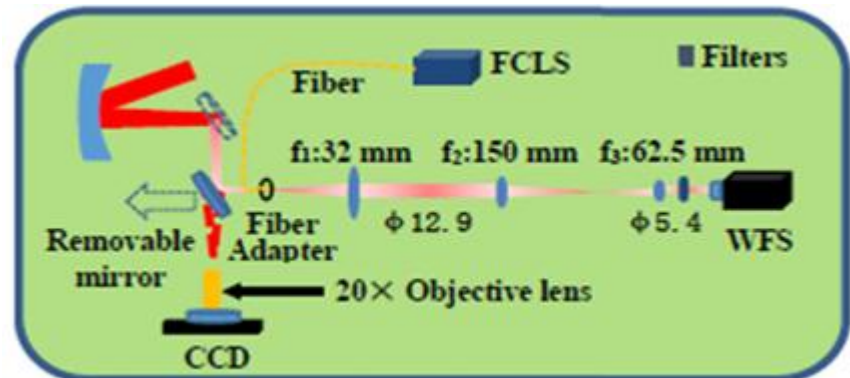
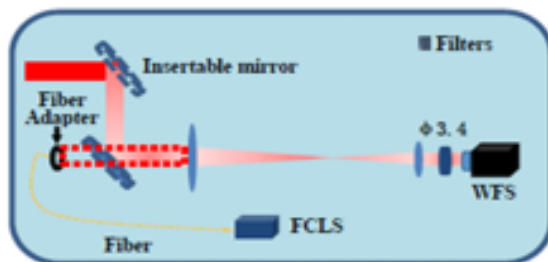
Flatness of the initial surface (P-V; RMS), μm	1.786; 0.355
Corrected mirror surface (P-V; RMS), no more than 20 % of control range of voltage applied, μm	0.061; 0.008
Number of control electrodes	64
Control voltage range, V	-300 ÷ +500
First resonance frequency, kHz	2.175
Operating frequency range, kHz	0 ÷ 1.0
Hysteresis, %	9
Reflecting coating	Multilayer dielectric
Maximal reflectivity ($\lambda=800\text{ nm}$), %	99.96
Reflectivity in the range from $800\pm 50\text{ nm}$, %	Not less than 99.82
Diameter of the substrate, mm	140
Optically used diameter, mm	130
Active aperture, mm	130
Substrate material	Glass LK-105
Thickness of the substrate, mm	4.0
Number of the piezo-discs	2
Diameter of the piezo-discs, mm	130
Thickness of the piezo-discs, mm	0.5
Dimensions of the holder (diameter x length), mm	$\varnothing 155 \times 64$
Weight in the holder, kg	1.2

WFC in amplification Stage

The position of first DM and sampling beam

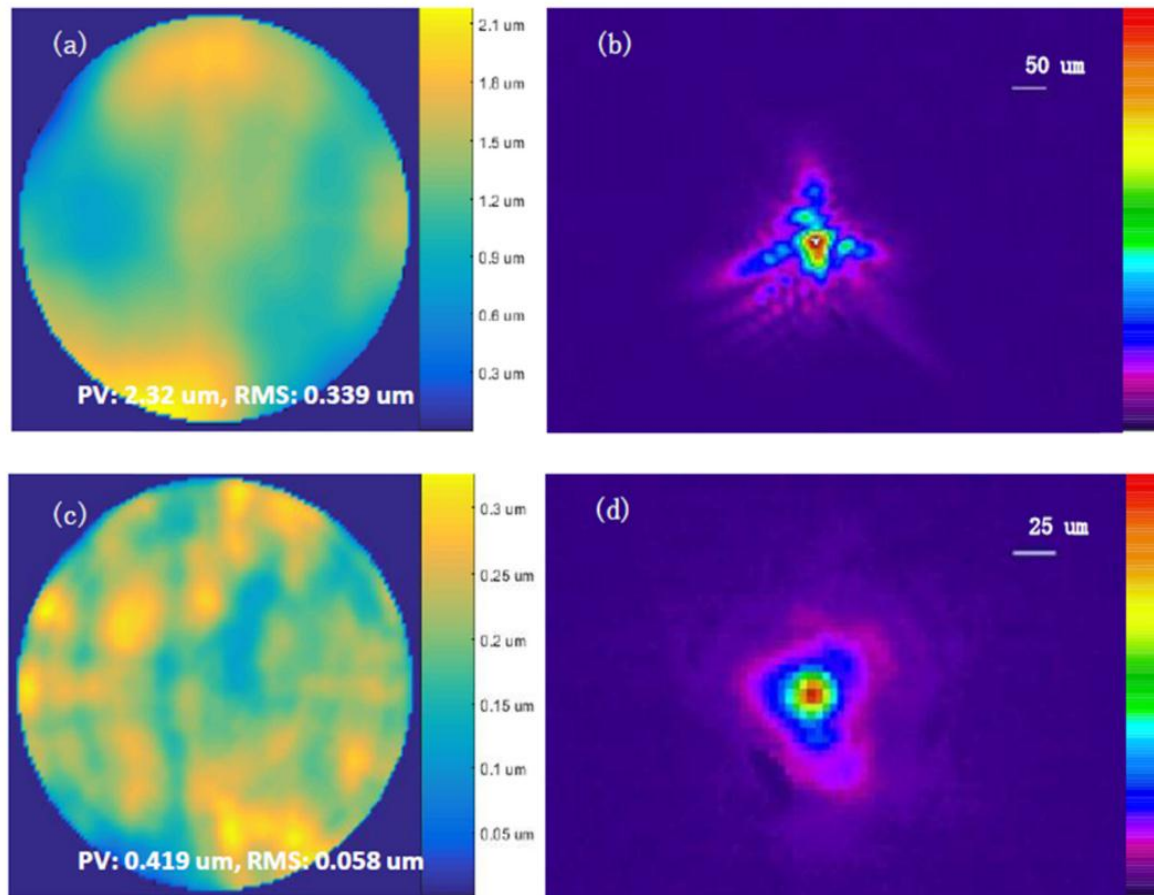


Measurement of wavefront and focus spot



FCLS: Fiber-Coupled Laser Source, an ideal point source was inserted in the focal position to measure and remove aberrations of the sampling optical path.

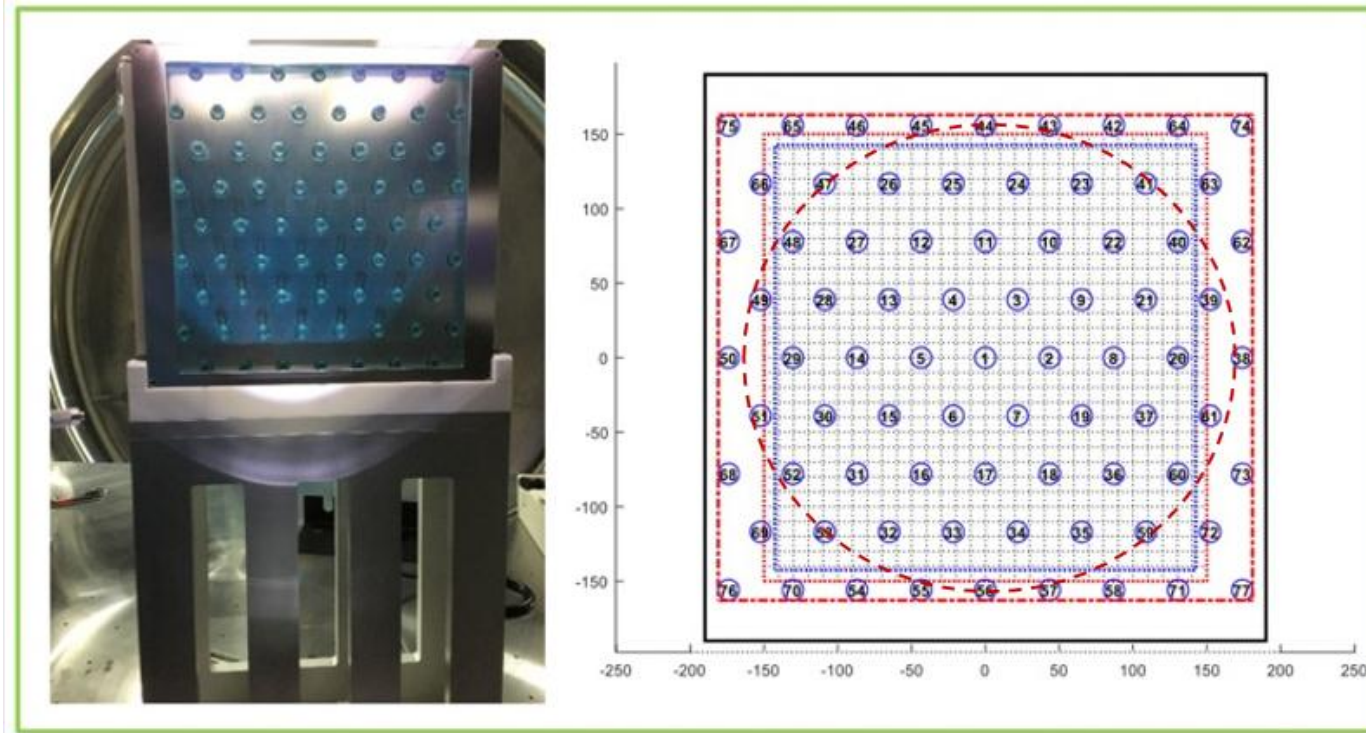
Results of WFC in amplification stage



The phase profiles of the laser beam (a) before and (c) after the correction; (b) and (d) the corresponding focal spots focused by the $f_4 = 2500$ mm lens.

Correction: pv: 2.32 μm \rightarrow 0.419 μm
RMS: 0.339 μm \rightarrow 0.058 μm

Deformable mirror - 2



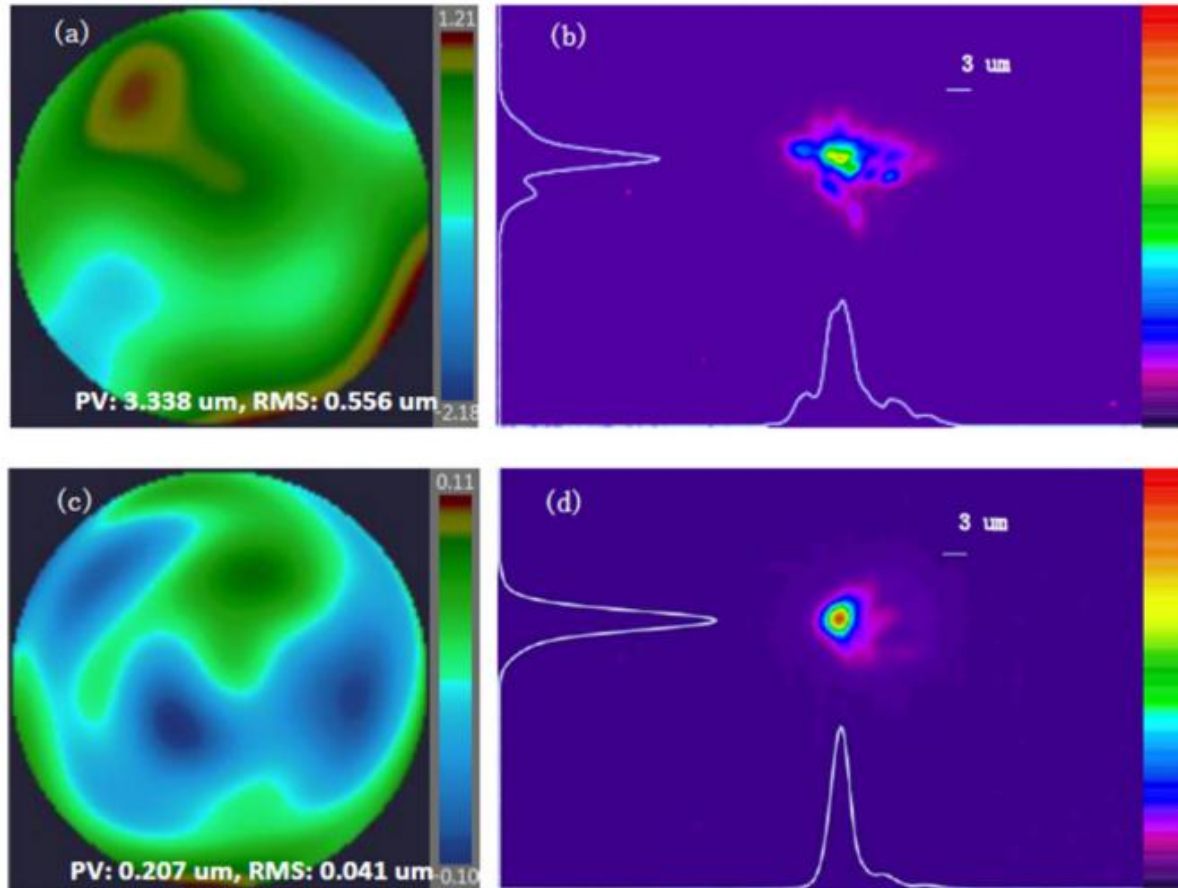
Effective aperture: 300mm*300mm

Number of control actuators: 77

Actuator type: Piezoelectric ceramics

Produced by Institute of Optics and Electronics (IOE), CAS

Results of WFC in terminal stage



The focal spot is enlarged by a 20X objective lens and measured by a 12-bit CCD

RMS=0.556 μm

Experimental Schematic:

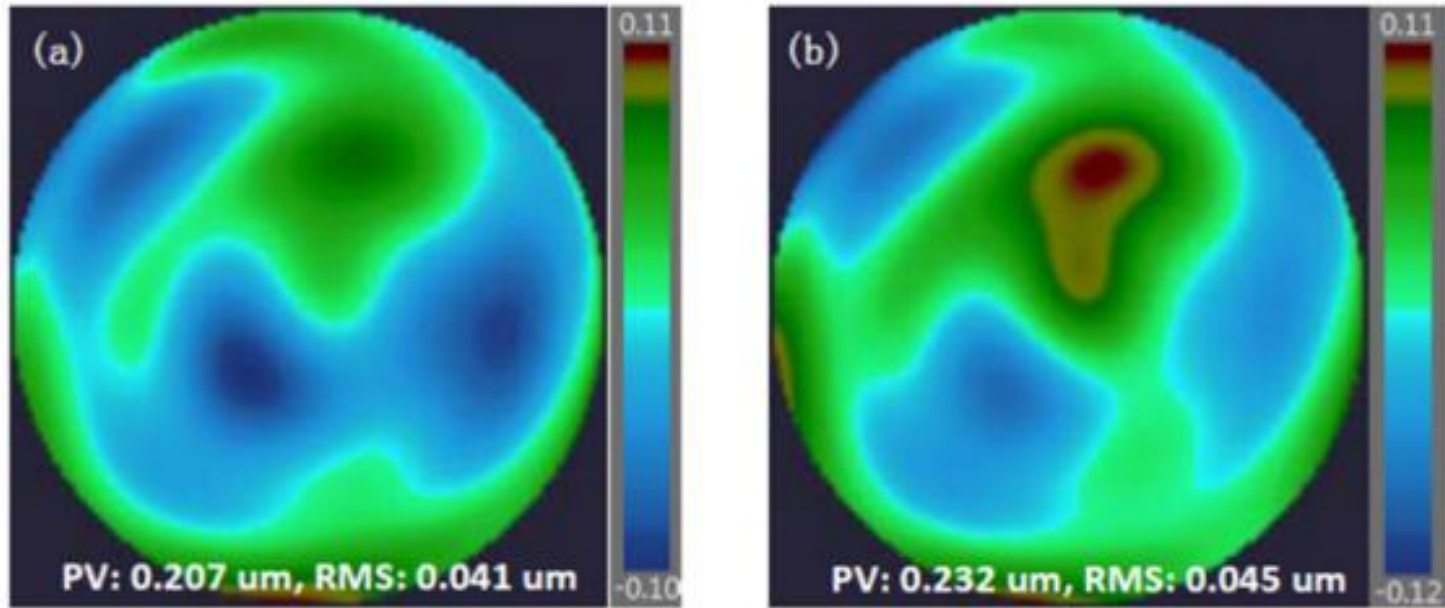
- DM1: $\phi 130\text{mm}$, after the Amp.V;
- DM2: $300\text{mm} \times 300\text{mm}$, after the compressor;
- OAP: F/2.5, $400\text{mm} \times 400\text{mm}$, $f=721\text{mm}$, $D_{\text{beam}}=290\text{mm}$; off-axis angle = 31°

Correction: pv: $3.338\mu\text{m} \rightarrow 0.207\mu\text{m}$
RMS: $0.556\mu\text{m} \rightarrow 0.041\mu\text{m}$



focus spot size: $2.75 \times 2.87 \mu\text{m}^2$

Wavefront for single shot amplification

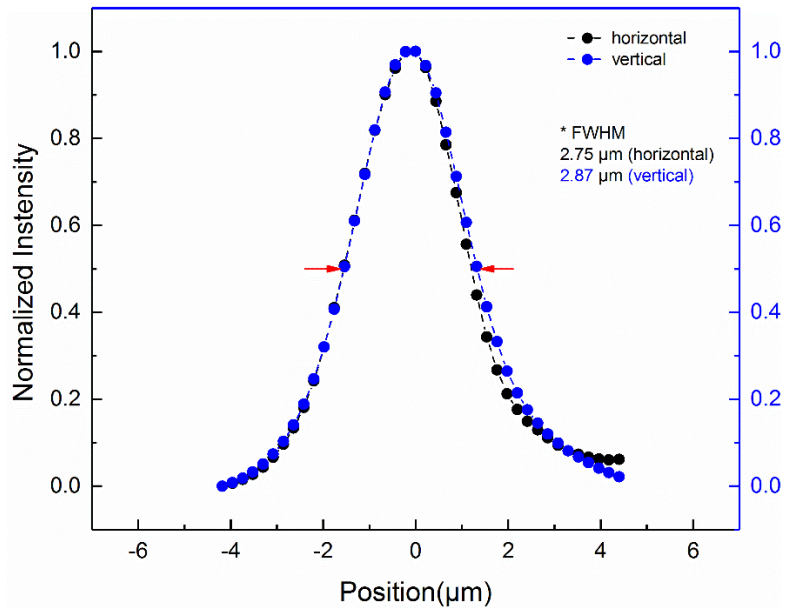


The phase profiles at point ⑤ : (a) measured at a frequency of 1 Hz; (b) measured at a single-shot amplified with an amplified energy of 40 J (after being attenuated by the high quality mirrors without coating).

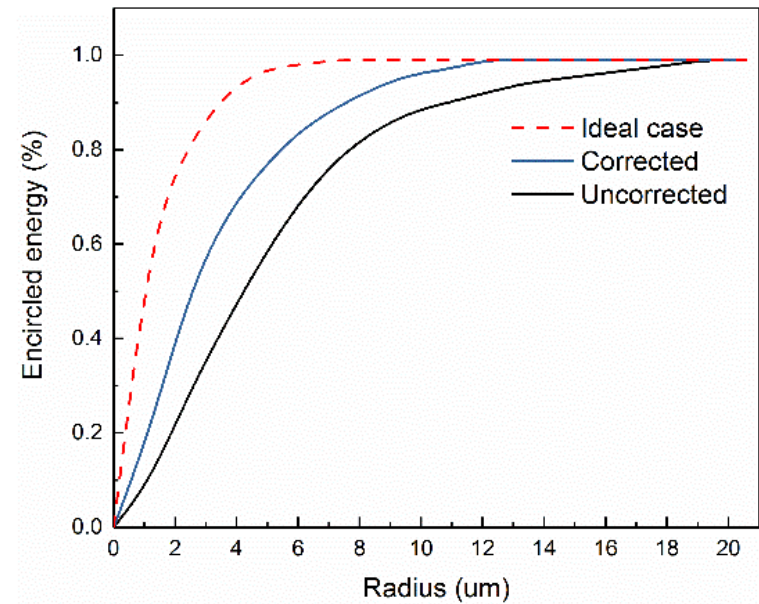
The RMS value of the single-shot amplified beam was 0.043– 0.05 μm, which was nearly the same as that measured in the frequency amplification.

Results of WFC in terminal stage

The distributions of the focal spot on the x and y-axes



The encircle energy curves



- ❑ The FWHM of the focal spot is $2.75 \times 2.87 \mu\text{m}$
- ❑ The focal spot of the measured plane contained approximately 27.69% energy in the FWHM area and 59.43% energy in the e^2 area.
- ❑ And, the peak intensity exceeded to $2 \times 10^{22} \text{ W/cm}^2$ with working distance of 721 mm (length of OAP)

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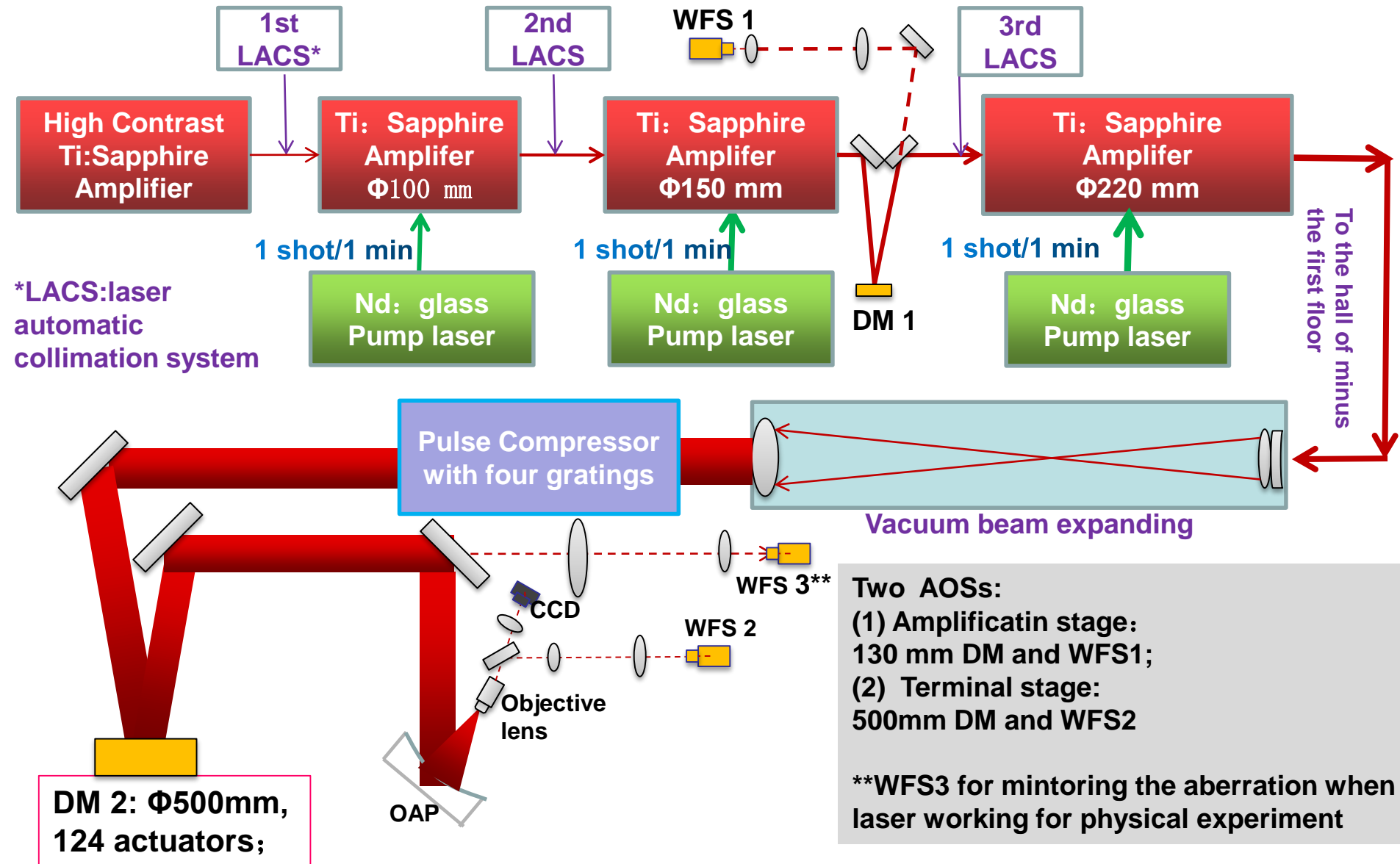
2 SULF Laser

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4 Wavefront correction of 10 PW

5 Summary

Diagram of SULF 10PW



Beam Expanders of SULF 10 PW

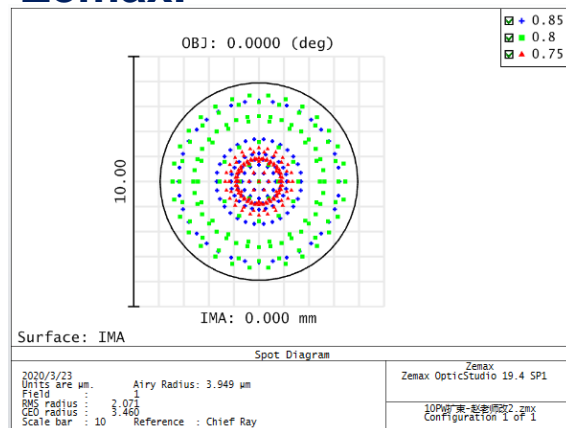
Four beam expanders based on achromatic lens were used to expand the beam size from 32 mm to 500 mm, and then into the 4-grating compressor. The expander were optimized design by Zemax.



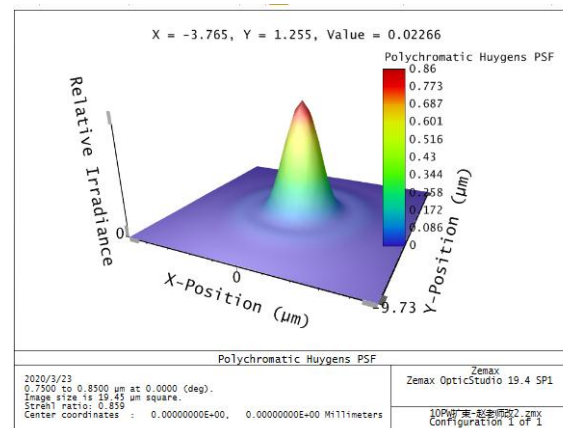
Φ 32mm Φ 120mm Φ 180mm

Φ 500mm

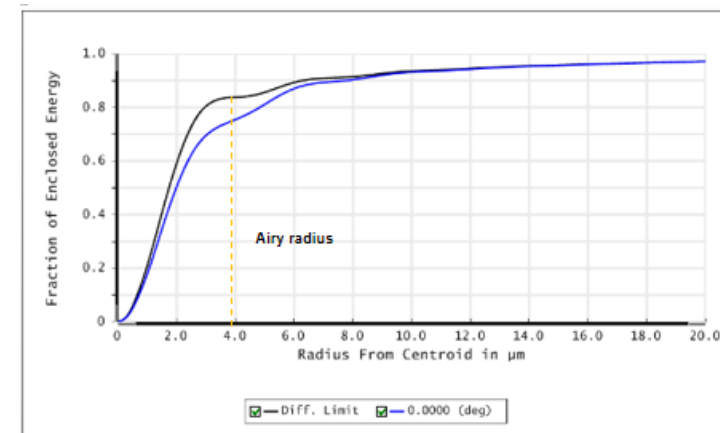
Optimization results: chromatic aberration causing by lens was optimized by Zemax.



Spot Diagram:
Airy radius: 3.949um
RMS radius: 2.071um
GEO radius: 3.460um



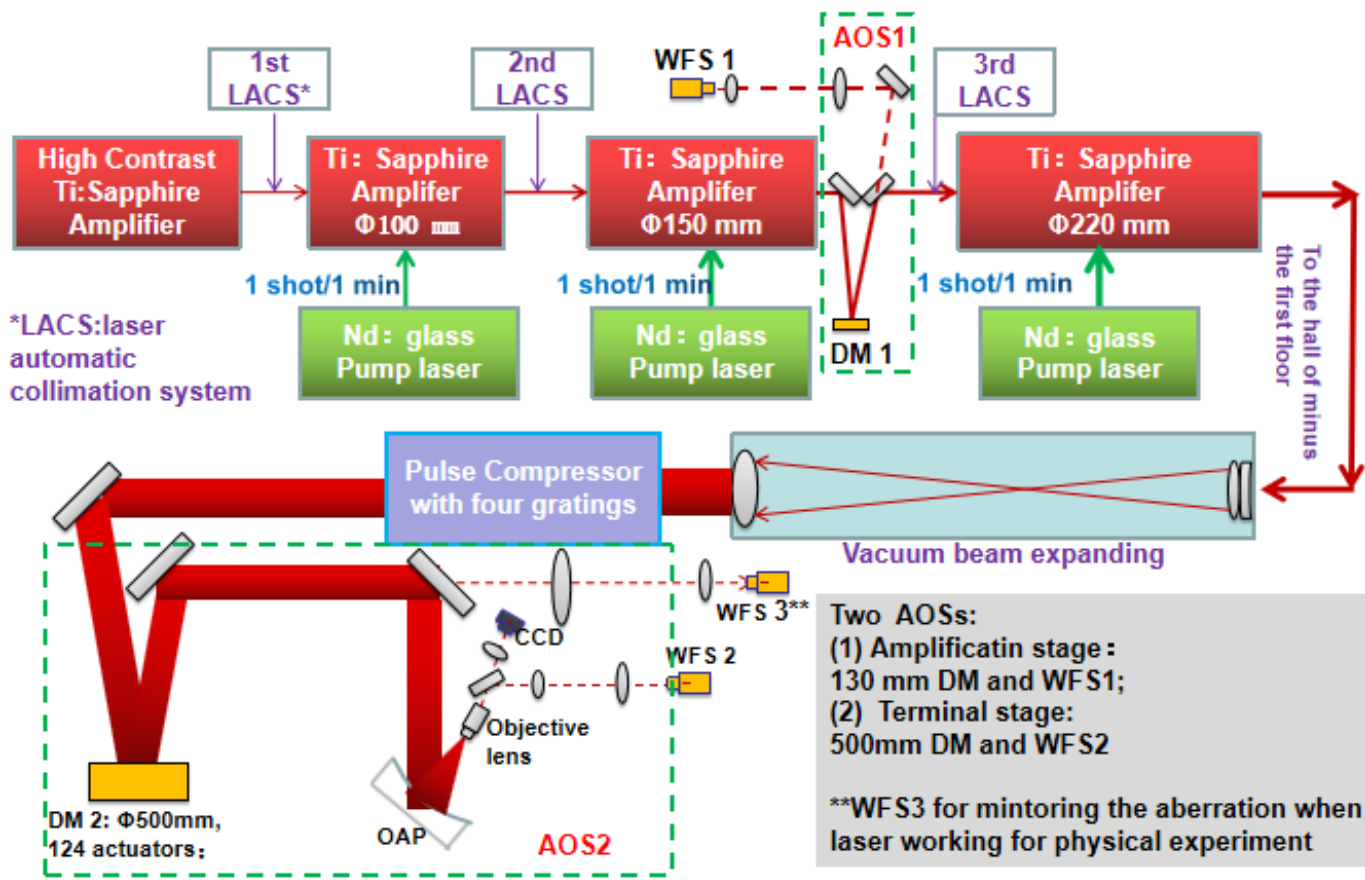
Huygens PSF:
Strehl rate: 0.859



Fraction of encircled energy

WFC and focusility of 10PW

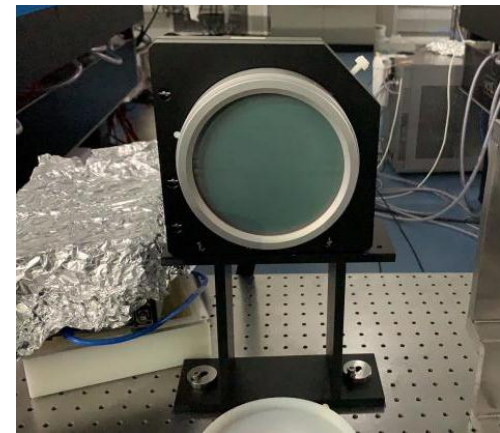
To improve the focusility of 10 PW laser pulse, two adaptive optics systems were used in SULF.



Two AOSs:
 (1) Amplificatin stage :
 130 mm DM and WFS1;
 (2) Terminal stage:
 500mm DM and WFS2

**WFS3 for mintoring the aberration when laser working for physical experiment

AOS1:130mm DM



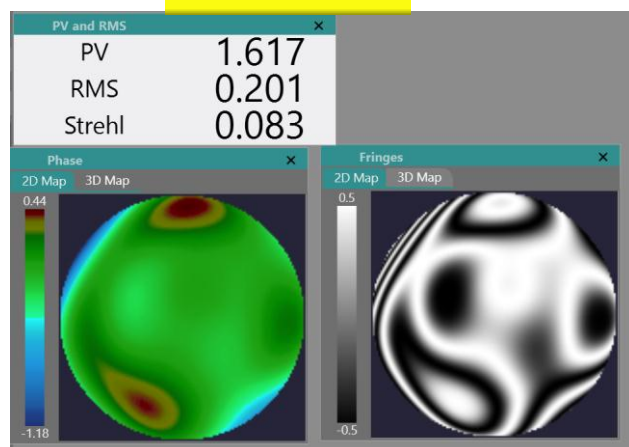
AOS2:500mm DM



AOS in amplifier stage

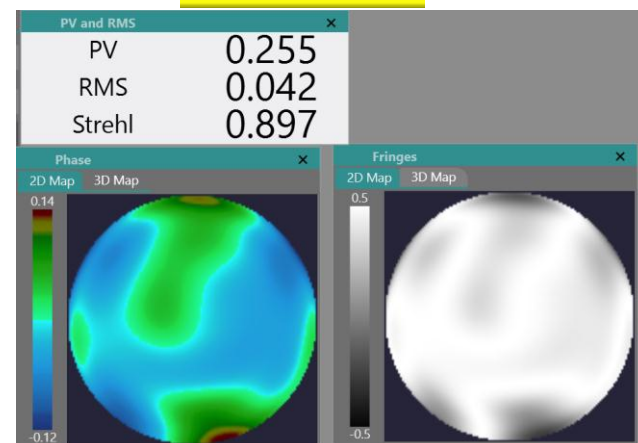
After correction of the first AOS in amplifier stage, the PV value was decreased from 1.6 μm to 0.255 μm and the RMS value from 0.255 μm to 0.042 μm . The strehl ratio was increased to 0.897.

AOS off

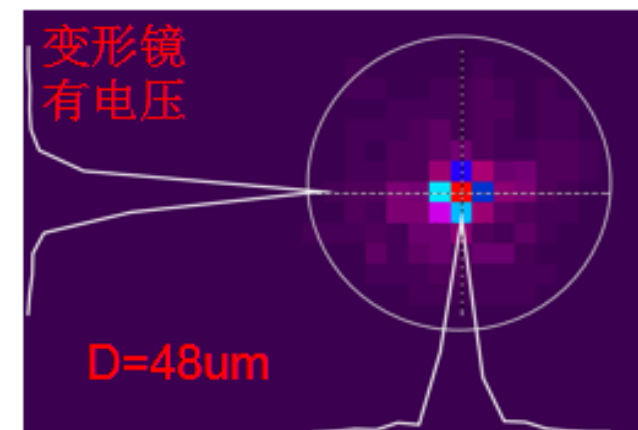
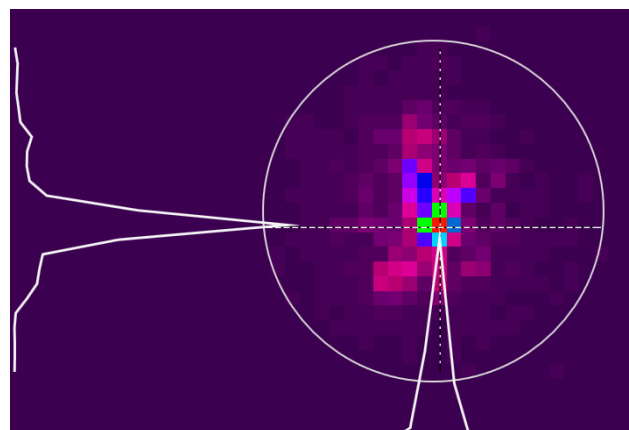


Wavefront map

OAS on



Focus spot

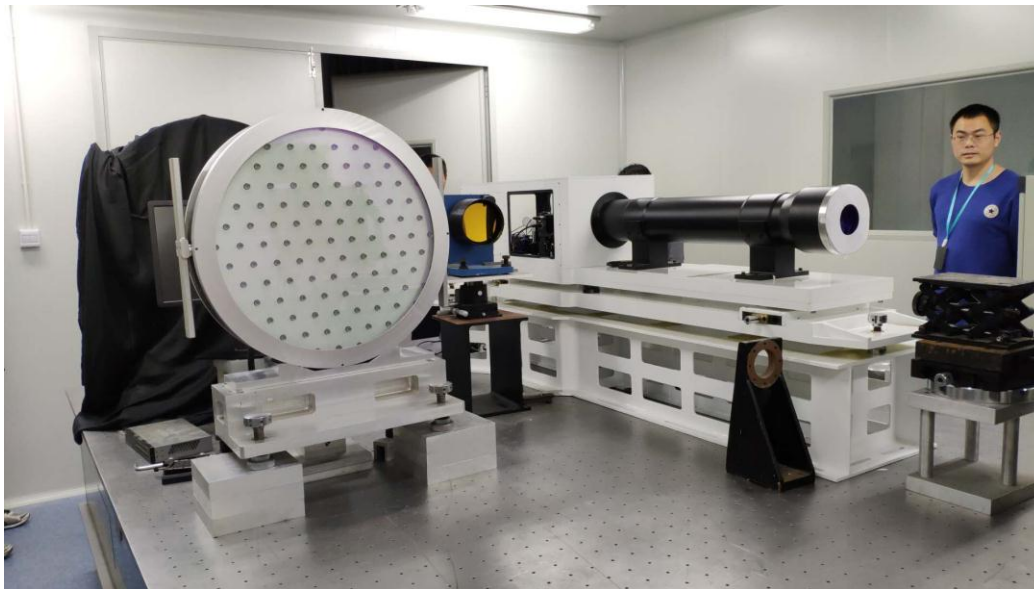


变形镜
有电压

D=48um

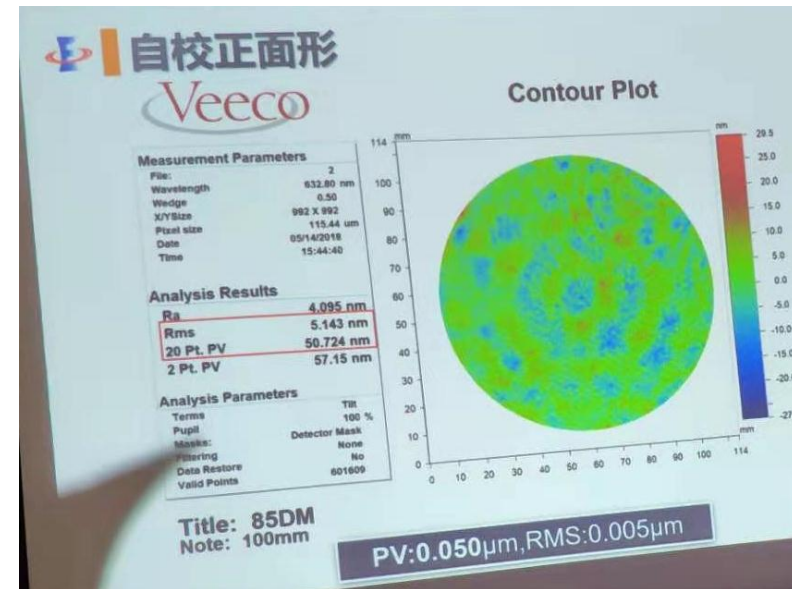
AOS in terminal stage

DM for terminal stage



Off-line measurement

Clear aperture: $\Phi 500\text{mm}$
Number of actuators: 124
Range: $\pm 7.5\mu\text{m}$

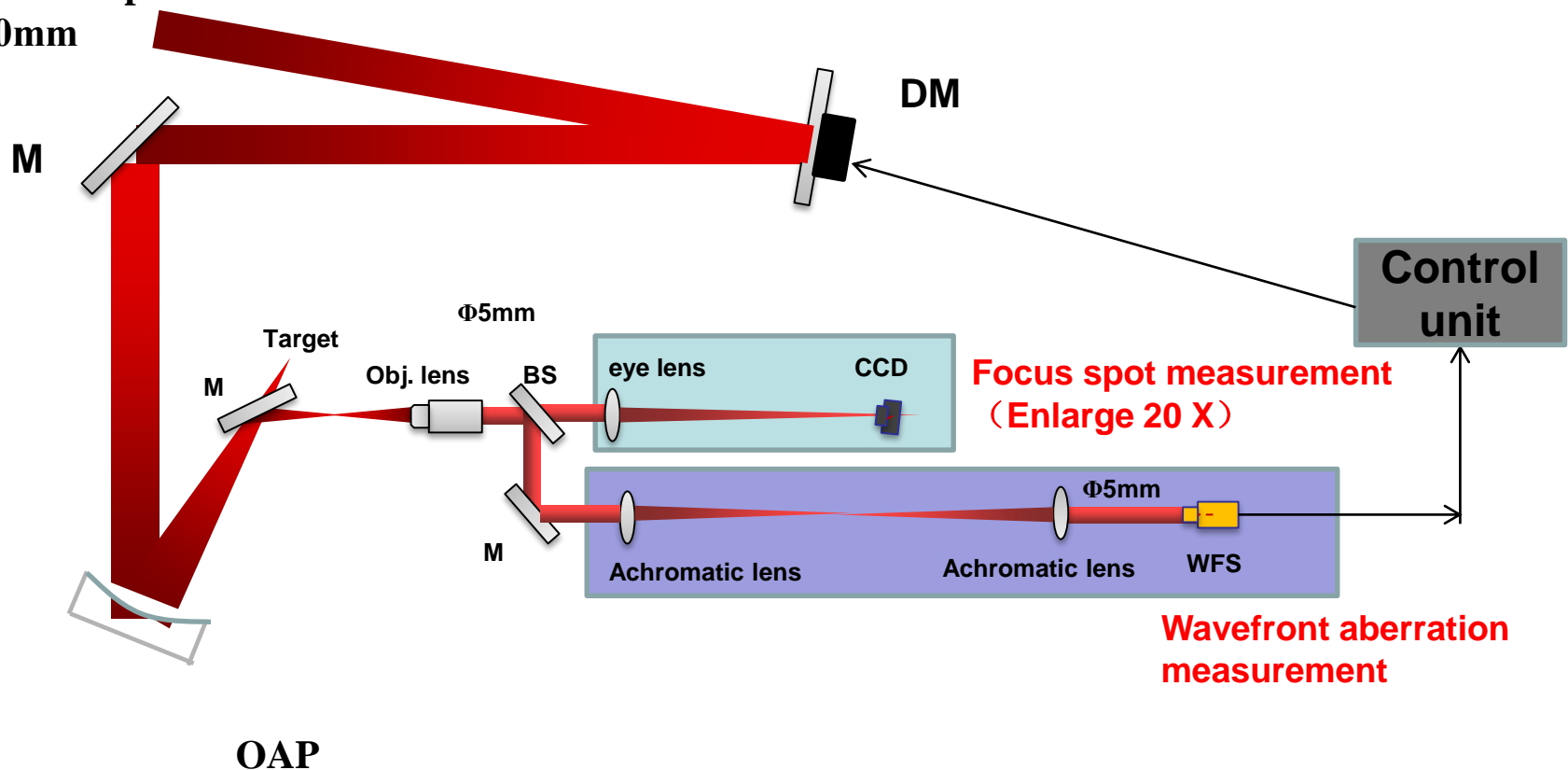


Result

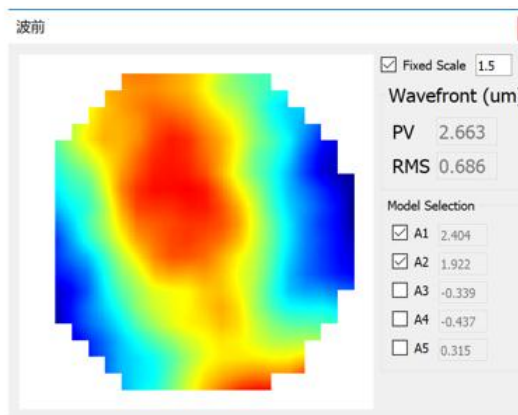
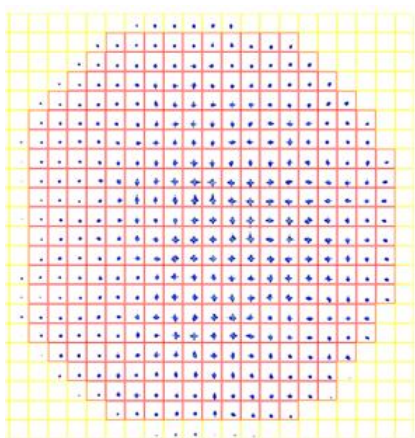
AOS in terminal stage

Optical path diagram of wavefront correction and focus measurement. It can measure the wavefront map and focus spot (20 X) of laser pulse at the same time. The deformable mirror and Hartmann are imaged by two stage image system. The objective lens and eye lens can enlarge the original focus spot of OAP by 20 times.

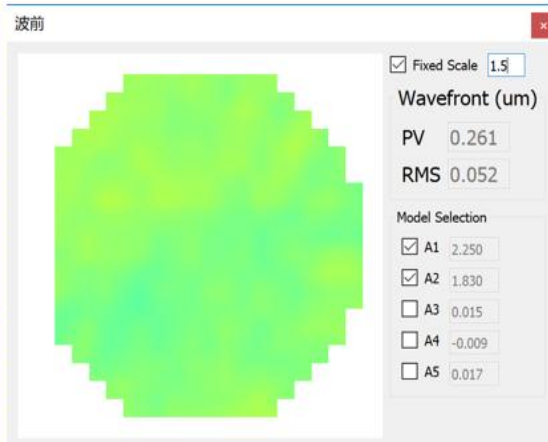
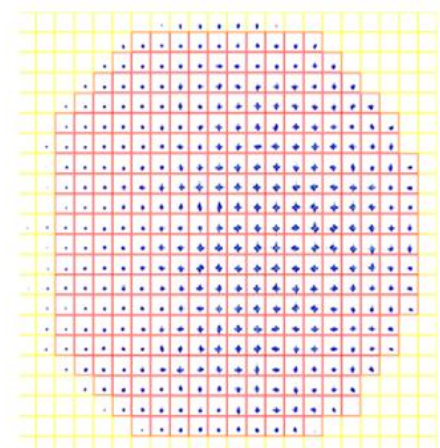
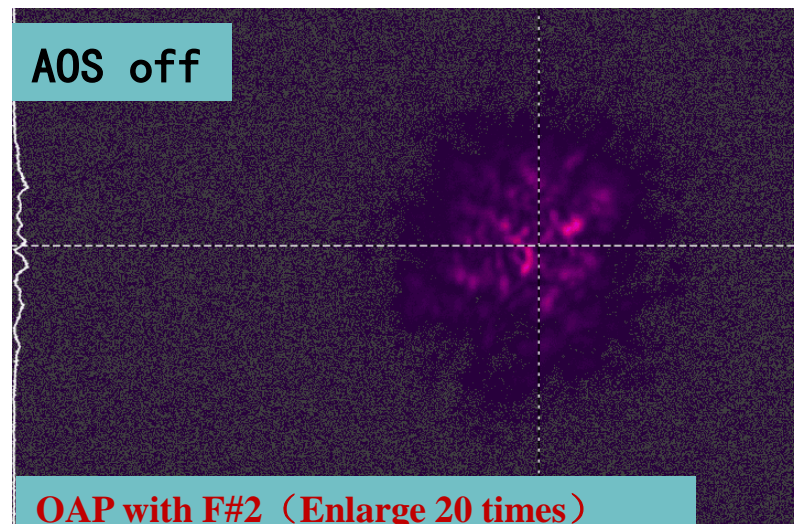
10PW Laser pulse
 $\Phi 500\text{mm}$



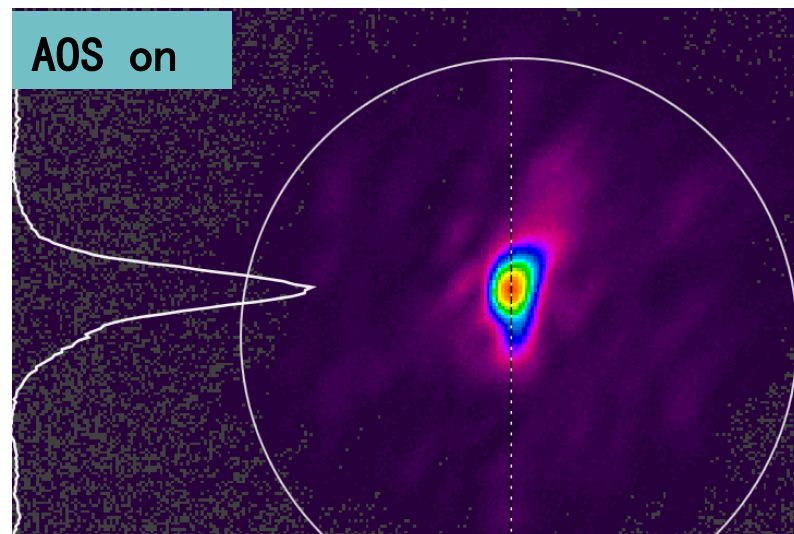
WFC and focusility of 10PW



AOS off: PV=2.663um, RMS=0.686um



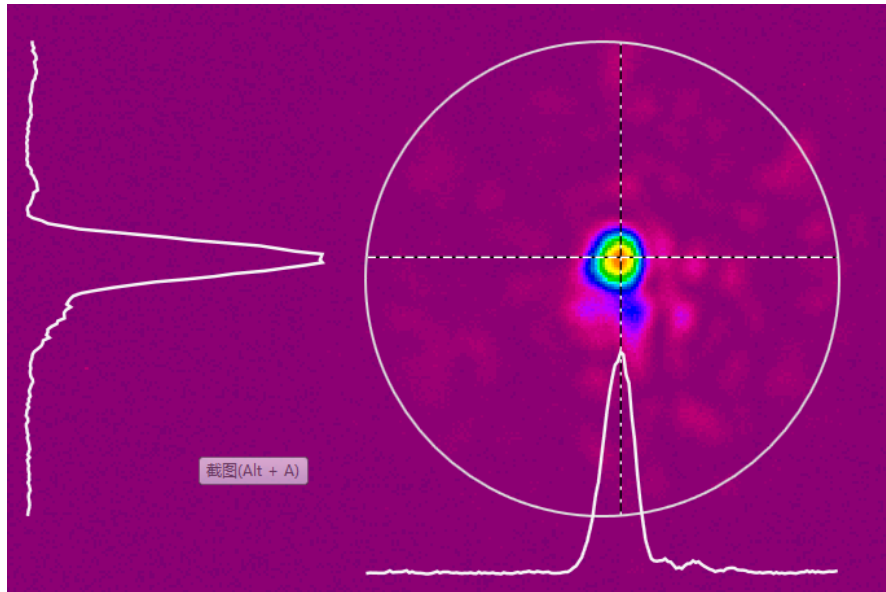
AOS on: PV=0.261um, RMS=0.052um



Focus Intensity $\sim 2.3 \times 10^{22} \text{W/cm}^2$

Focus with narrow bandwidth filter

With $800\text{nm} \pm 10\text{nm}$ filter



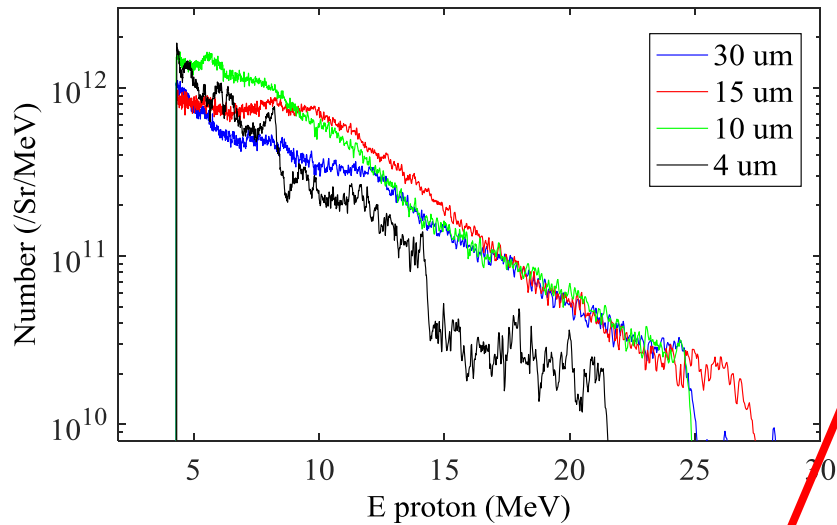
Beam size: $2.5\mu\text{m}$ (FWHM),
Encircled energy $\sim 26.14\%$,
Encircled energy in $1/e^2 > 45\%$

Proton acceleration

Laser Parameters : 60 J/30 fs, 2PW

Target : 15 μm -thickness Cu,

Proton Energy



63

30 μm Cu 25MeV

64

15 μm Cu 27MeV

65

10 μm Cu 24.8MeV

66

4 μm Cu 21.4MeV

Proton Numbers

Proton spectrum
intergral

Energy interval

Number of Proton

Size of Proton
source

10-20 MeV

1.8e+5

7 μm \times 10 μm

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3 Wavefront correction of 5.4 PW

4 Wavefront correction of 10 PW

5 Summary

Summary

- **Two adaptive optics systems are used in SULF 10 PW laser facility to optimize the wavefront aberration and improve the focus intensity;**
- **The corrected beam is focused to $2.75 \times 2.87 \text{ um}^2$ at FWHM with a long focal length OAP (f=721mm) in the year of 2018. A peak intensity of $2 \times 10^{22} \text{ W/cm}^2$ is achieved at the output of 5.4 PW .**
- **In 10 PW laser facility, the focus spot size after correction is $2.4\text{um} \times 2.9\text{um}$ (F#2 OAP) and encircled energy is 28.9% in $\Phi 4 \text{ um}$. The focus intensity is $\sim 2.3 \times 10^{22} \text{ W/cm}^2$ at present.**
- **In future, focus spot will be optimized (for example:angular chirp, chromatic aberration and measurement of focus, etc) and intensity will be up to 10^{23} W/cm^2 with OAP of F#2. And some interesting experiment will be carried out with intensity of $10^{22} \sim 10^{23} \text{ W/cm}^2$**



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中国科学院上海光学精密机械研究所
Shanghai Institute of Optics and Fine Mechanics, CAS

Thank you